



STIC Search Report

EIC 1700

STIC Database Tracking Number: 207550

TO: Duc Truong
Location: Remsen 10d71
Art Unit : 1711
November 16, 2006
Phone: 571-272-1081
Serial Number: 10 / 517042

From: Jan Delaval
Location: EIC 1700
Remsen 4a30
Phone: 571-272-2504

jan.delaval@uspto.gov

Search Notes

Access DB# 204550

SEARCH REQUEST FORM

Scientific and Technical Information Center

Requester's Full Name: TRINZ INC Examiner #: 69332 Date: 11/15/86
 Art Unit: 1711 Phone Number 302-1281 Serial Number: 10/117,042
 Mail Box and Bldg/Room Location: 6D71 Results Format Preferred (circle): PAPER DISK E-MAIL

If more than one search is submitted, please prioritize searches in order of need.

 Please provide a detailed statement of the search topic, and describe as specifically as possible the subject matter to be searched. Include the elected species or structures, keywords, synonyms, acronyms, and registry numbers, and combine with the concept or utility of the invention. Define any terms that may have a special meaning. Give examples or relevant citations, authors, etc, if known. Please attach a copy of the cover sheet, pertinent claims, and abstract.

Title of Invention: _____

Inventors (please provide full names): _____

Earliest Priority Filing Date: _____

**For Sequence Searches Only* Please include all pertinent information (parent, child, divisional, or issued patent numbers) along with the appropriate serial number.*

Formula I_b or I_c in claim 1, derived from the process in claim 8
Thanks.

STAFF USE ONLY

	Type of Search	Vendors and cost where applicable
Searcher: <u>ga</u>	NA Sequence (#) _____	STN <u>1</u>
Searcher Phone #: <u>22504</u>	AA Sequence (#) _____	Dialog _____
Searcher Location: _____	Structure (#) <u>✓</u>	Questel/Orbit _____
Date Searcher Picked Up: <u>11/16/86</u>	Bibliographic _____	Dr.Link _____
Date Completed: <u>11/16/86</u>	Litigation _____	Lexis/Nexis _____
Searcher Prep & Review Time: _____	Fulltext _____	Sequence Systems _____
Clerical Prep Time: <u>20</u>	Patent Family _____	WWW/Internet _____
Online Time: <u>486</u>	Other _____	Other (specify) _____

=> fil reg

FILE 'REGISTRY' ENTERED AT 07:59:10 ON 16 NOV 2006
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STRUCTURE FILE UPDATES: 15 NOV 2006 HIGHEST RN 913321-83-2
DICTIONARY FILE UPDATES: 15 NOV 2006 HIGHEST RN 913321-83-2

New CAS Information Use Policies, enter HELP USAGETERMS for details.

TSCA INFORMATION NOW CURRENT THROUGH June 30, 2006

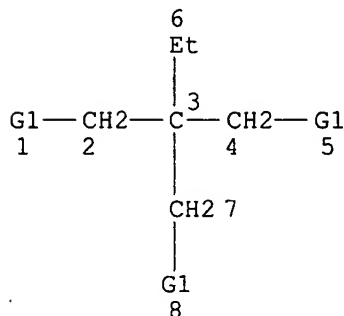
Please note that search-term pricing does apply when
conducting SmartSELECT searches.

REGISTRY includes numerically searchable data for experimental and
predicted properties as well as tags indicating availability of
experimental property data in the original document. For information
on property searching in REGISTRY, refer to:

<http://www.cas.org/ONLINE/UG/regprops.html>

=> d sta que 150

L21 STR



VAR G1=O/X

NODE ATTRIBUTES:

DEFAULT MLEVEL IS ATOM

DEFAULT ECLEVEL IS LIMITED

GRAPH ATTRIBUTES:

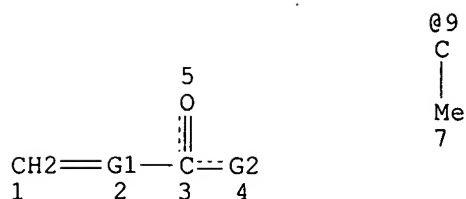
RING(S) ARE ISOLATED OR EMBEDDED

NUMBER OF NODES IS 8

STEREO ATTRIBUTES: NONE

L23 35943 SEA FILE=REGISTRY SSS FUL L21

L24 STR



VAR G1=CH/9

VAR G2=O/X

NODE ATTRIBUTES:

DEFAULT MLEVEL IS ATOM

DEFAULT ECLEVEL IS LIMITED

GRAPH ATTRIBUTES:

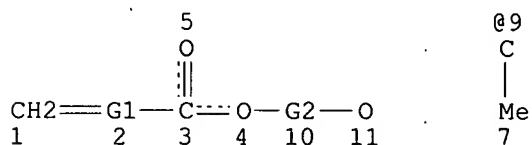
RING(S) ARE ISOLATED OR EMBEDDED

NUMBER OF NODES IS 7

STEREO ATTRIBUTES: NONE

L26 15579 SEA FILE=REGISTRY SUB=L23 SSS FUL L24

L46 STR



VAR G1=CH/9

VAR G2=AK/ID

NODE ATTRIBUTES:

CONNECT IS M1 RC AT 11

DEFAULT MLEVEL IS ATOM

DEFAULT ECLEVEL IS LIMITED

GRAPH ATTRIBUTES:

RING(S) ARE ISOLATED OR EMBEDDED

NUMBER OF NODES IS 9

STEREO ATTRIBUTES: NONE

L48 SCR 1992 OR 2021 OR 2016 OR 2026 OR 1852 OR 1855 OR 1867

L50 1830 SEA FILE=REGISTRY SUB=L26 CSS FUL L46 NOT L48

100.0% PROCESSED 4075 ITERATIONS

1830 ANSWERS

SEARCH TIME: 00.00.01

=> d sta que 118

L4 17006 SEA FILE=REGISTRY ABB=ON PLU=ON 77-99-6/CRN

L5 1559 SEA FILE=REGISTRY ABB=ON PLU=ON L4 AND (79-10-7 OR 79-41-4)/C
RN

L6 215 SEA FILE=REGISTRY ABB=ON PLU=ON L5 AND C2H4O

L7 104 SEA FILE=REGISTRY ABB=ON PLU=ON L6 AND C3H6O

L8 98 SEA FILE=REGISTRY ABB=ON PLU=ON L7 AND 75-21-8/CRN

L10 97 SEA FILE=REGISTRY ABB=ON PLU=ON L8 AND 75-56-9/CRN

L11 2 SEA FILE=REGISTRY ABB=ON PLU=ON L8 AND (31714-45-1 OR
25322-69-4)/CRN

L12 98 SEA FILE=REGISTRY ABB=ON PLU=ON (L10 OR L11)
 L14 39 SEA FILE=REGISTRY ABB=ON PLU=ON L12 NOT C6/ES
 L15 36 SEA FILE=REGISTRY ABB=ON PLU=ON L14 NOT 56-81-5/CRN
 L16 34 SEA FILE=REGISTRY ABB=ON PLU=ON L15 NOT OC4-C6/ES
 L17 13 SEA FILE=REGISTRY ABB=ON PLU=ON (103694-74-2/BI OR 111236-63-
 6/BI OR 111320-36-6/BI OR 117742-97-9/BI OR 117801-93-1/BI OR
 148652-11-3/BI OR 148652-12-4/BI OR 607391-97-9/BI OR 67184-00-
 3/BI OR 774577-50-3/BI OR 774577-52-5/BI OR 774580-85-7/BI OR
 774580-94-8/BI)
 L18 21 SEA FILE=REGISTRY ABB=ON PLU=ON L16 NOT L17

=> d his

(FILE 'HOME' ENTERED AT 06:38:22 ON 16 NOV 2006)
 SET COST OFF

FILE 'HCAPLUS' ENTERED AT 06:38:40 ON 16 NOV 2006

L1 7 S US20050215752/PN OR (US2004-517042# OR WO2003-EP5953 OR DE200
 SEL RN

FILE 'REGISTRY' ENTERED AT 06:40:04 ON 16 NOV 2006

L2 75 S E1-E75
 L3 1 S L2 AND C6H14O3/MF
 L4 17006 S 77-99-6/CRN
 L5 1559 S L4 AND (79-10-7 OR 79-41-4)/CRN
 L6 215 S L5 AND C2H4O
 L7 104 S L6 AND C3H6O
 L8 98 S L7 AND 75-21-8/CRN
 L9 0 S L7 AND 25322-68-3/CRN
 L10 97 S L8 AND 75-56-9/CRN
 L11 2 S L8 AND (31714-45-1 OR 25322-69-4)/CRN
 L12 98 S L10,L11
 L13 6 S L7 NOT L12
 L14 39 S L12 NOT C6/ES
 L15 36 S L14 NOT 56-81-5/CRN
 L16 34 S L15 NOT OC4-C6/ES
 SEL RN 4 5 8 9 14 17 18 25 27 29-31 33
 L17 13 S E76-E88
 L18 21 S L16 NOT L17
 L19 16 S L2 AND L4
 L20 6 S L19 NOT L18
 SAV L18 TRUONG517/A
 L21 STR
 L22 50 S L21
 L23 35943 S L21 FUL
 L24 STR
 L25 50 S L24 SAM SUB=L23
 L26 15579 S L24 FUL SUB=L23
 L27 499 S L26 AND (75-21-8 OR 25322-68-3)/CRN
 L28 2681 S L26 AND C2H4O
 L29 2681 S L27,L28
 L30 266 S L29 AND (75-56-9 OR 31714-45-1 OR 25322-69-4)/CRN
 L31 431 S L29 AND C3H6O
 L32 431 S L30,L31
 L33 154 S L32 NOT (C6 OR OC4-C6)/ES
 L34 117 S L33 NOT L12
 L35 111 S L34 NOT OC4/ES
 L36 39 S L35 AND (N OR S OR SI OR P)/ELS
 L37 72 S L35 NOT L36

L38 70 S L37 NOT 56-81-5/CRN
 L39 65 S L38 NOT C4H4O4
 L40 34 S L39 NOT (UNSPECIFIED OR C5-C6-C6-C6/ES)
 L41 6 S L40 AND NR>=3
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 SEL RN 2 4-9 11 16 18 19 21 23-28
 L43 10 S L42 NOT E89-E106
 L44 STR L24
 L45 50 S L44 SAM SUB=L26
 L46 STR L44
 L47 50 S L46 CSS SAM SUB=L26
 L48 SCR 1992 OR 2021 OR 2016 OR 2026 OR 1852 OR 1855 OR 1867
 L49 50 S L46 NOT L48 CSS SAM SUB=L26
 L50 1830 S L46 NOT L48 CSS FUL SUB=L26
 L51 1762 S L50 NOT (C6-C6 OR C5-C6 OR OC4-C6)/ES
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 L53 336 S L52 NOT UNSPECIFIED
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 L56 21 S L55 CSS SAM SUB=L50
 L57 427 S L55 CSS FUL SUB=L50
 L58 135 S L57 AND (C2H4O OR C3H6O)
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 L60 3 S L59 AND C15H24O6 NOT UNSPECIFIED
 SEL RN 1
 L61 1 S E107
 L62 111 S L58 NOT L59
 L63 57 S L62 NOT UNSPECIFIED
 SEL RN 5 15 19 30 32 34 48
 L64 7 S E108-E114
 L65 37 S L18,L43,L61,L64
 L66 47 S L2 AND PMS/CI
 L67 37 S L66 NOT L65
 L68 29 S L67 NOT 56-81-5/CRN
 SEL RN 2 8
 L69 2 S E115-E116
 L70 39 S L65,L69
 L71 28 S L2 NOT L66,L70
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FILE 'HCAPLUS' ENTERED AT 07:51:53 ON 16 NOV 2006

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 L74 8 S L72 AND BASF?/PA,CS
 L75 8 S L73,L74
 L76 3 S L72 NOT P/DT
 L77 30 S L72 NOT L75,L76
 L78 26 S L77 AND (PD<=20030606 OR PRD<=20030606 OR AD<=20030606)
 L79 26 S L77 AND (PD<=20020611 OR PRD<=20020611 OR AD<=20020611)
 L80 29 S L76,L78,L79
 L81 4 S L77 NOT L80
 SEL RN L75

FILE 'REGISTRY' ENTERED AT 07:55:49 ON 16 NOV 2006

L82 90 S E117-E206
 L83 28 S L82 NOT L2
 L84 8 S L83 AND L4
 L85 5 S L84 NOT C6/ES
 L86 3 S L85 NOT (117801-97-5 OR 117801-93-1)

FILE 'HCAPLUS' ENTERED AT 07:58:08 ON 16 NOV 2006

L87 2 S L86
 L88 37 S L87,L75,L80
 L89 8 S L88 AND L75
 L90 29 S L88 NOT L89
 L91 8 S L89 AND (PD<=20020611 OR PRD<=20020611 OR AD<=20020611)

FILE 'REGISTRY' ENTERED AT 07:59:10 ON 16 NOV 2006

=> fil hcaplus

FILE 'HCAPLUS' ENTERED AT 07:59:48 ON 16 NOV 2006

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FILE COVERS 1907 - 16 Nov 2006 VOL 145 ISS 21

FILE LAST UPDATED: 15 Nov 2006 (20061115/ED)

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This file contains CAS Registry Numbers for easy and accurate substance identification.

=> d l91 bib abs hitstr retable tot

L91 ANSWER 1 OF 8 HCAPLUS COPYRIGHT 2006 ACS on STN

AN 2004:857643 HCAPLUS

DN 141:350865

TI Mixtures of polyalkoxylated trimethylolpropane (meth)acrylates for crosslinked hydrogel manufacturing.

IN Popp, Andreas; Daniel, Thomas; Schroeder, Juergen; Jaworek, Thomas; Funk, Ruediger; Schwalm, Reinhold; Weismantel, Matthias; Riegel, Ulrich

PA BASF Aktiengesellschaft, Germany

SO PCT Int. Appl., 61 pp.

CODEN: PIXXD2

DT Patent

LA German

FAN.CNT 8

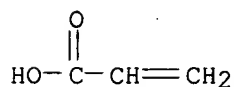
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TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW
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 TD, TG
 WO 2003104300 A1 20031218 WO 2003-EP305953 20030606 <--
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 CA 2520719 AA 20041014 CA 2004-2520719 20040402
 EP 1613685 A2 20060111 EP 2004-725321 20040402
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 IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, PL, SK, HR
 BR 2004009007 A 20060328 BR 2004-9007 20040402
 JP 2006524275 T2 20061026 JP 2006-504980 20040402
 US 2006212011 A1 20060921 US 2005-551630 20051104
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 DE 2003-10315669 A 20030404
 WO 2003-EP5953 A 20030606
 DE 2002-10225943 A 20020611 <--
 WO 2003-EP305953 A 20030606
 WO 2004-EP3551 W 20040402
 OS MARPAT 141:350865
 GI

* STRUCTURE DIAGRAM TOO LARGE FOR DISPLAY - AVAILABLE VIA OFFLINE PRINT *

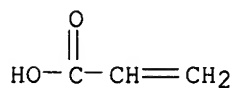
AB A mixture of ≥ 2 polyalkoxylated trimethylolpropane (meth)acrylates I, II, III (AO1, AO2 and AO3 = EO, PO or/and BO, EO = OCH₂CH₂, PO = OCH₂CHCH₃ or OCH(CH₃)CH₂, BO = OCH₂CH₂Et or OCH(Et)CH₂, p1 + p2 + p3 = 28 - 75, n1 + n2 + n3 = 28 - 60, m1 + m2 + m3 = 4 - 13, R1, R2 and R3 = H or CH₃) prepared by reacting a mixture of alkoxyated trimethylolpropanes with (meth)acrylic acid in the presence of ≥ 1 esterification catalyst and ≥ 1 polymerization inhibitor is used as crosslinking agent for manufacture of a swellable crosslinked hydrogel (superabsorbing polymer), as raw material for paints, as additives to cement and for polymer dispersion and polyacrylates manufacture Hydrogel manufacture comprises steps of (a) radical polymerization of an ester mixture with (meth)acrylic acid optionally in the presence of monoethylenically unsatd. compds., hydrophilic monomers (such as sodium acrylate) and radical initiators, (b) drying and (c) milling of the resulting mixture This, mixing 1427 weight parts of ethoxylated and propoxylated trimethylolpropane, 216 weight parts of acrylic acid, 5 weight parts of H₂SO₄ in 345 weight parts of methylcyclohexane, adding 3 weight parts of hydroquinone monomethyl ether, 1 weight part of triphenylphosphite, 1 weight part of hypophosphoric acid gave (after removing an azeotropic water) a polymer having viscosity 330 mPa s, used as a crosslinking agent for acrylic acid

IT and sodium acrylate for swellable hydrogel manufacturing
 824950-59-6P
 RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
 (crosslinked hydrogel; mixture of polyalkoxylated trimethylolpropane (meth)acrylates for swellable crosslinked hydrogel (superabsorbing polymer) manufacture)
 RN 824950-59-6 HCAPLUS
 CN 2-Propenoic acid, polymer with methyloxirane diblock polymer with oxirane ether with 2-ethyl-2-(hydroxymethyl)-1,3-propanediol (3:1) tri-2-propenoate, and sodium 2-propenoate (9CI) (CA INDEX NAME)
 CM 1
 CRN 7446-81-3
 CMF C3 H4 O2 . Na



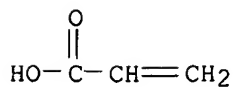
● Na

CM 2
 CRN 79-10-7
 CMF C3 H4 O2



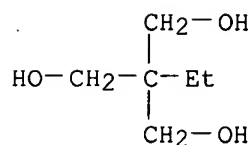
CM 3
 CRN 824950-31-4
 CMF C6 H14 O3 . 3 (C3 H6 O . C2 H4 O)x . 3 C3 H4 O2

CM 4
 CRN 79-10-7
 CMF C3 H4 O2



CM 5
 CRN 77-99-6

CMF C6 H14 O3



CM 6

CRN 697765-47-2

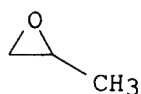
CMF (C3 H6 O . C2 H4 O)x

CCI PMS

CM 7

CRN 75-56-9

CMF C3 H6 O



CM 8

CRN 75-21-8

CMF C2 H4 O



IT 824950-31-4P

RL: IMF (Industrial manufacture); RCT (Reactant); PREP (Preparation); RACT (Reactant or reagent)

(polyalkoxylated trimethylolpropane (meth)acrylates; mixture of polyalkoxylated trimethylolpropane (meth)acrylates for swellable crosslinked hydrogel (superabsorbing polymer) manufacture)

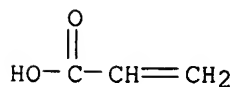
RN 824950-31-4 HCAPLUS

CN Oxirane, methyl-, polymer with oxirane, ether with 2-ethyl-2-(hydroxymethyl)-1,3-propanediol (3:1), tri-2-propenoate, diblock (9CI) (CA INDEX NAME)

CM 1

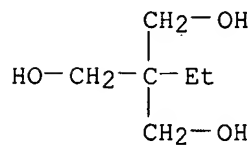
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CMF C3 H4 O2



CM 2

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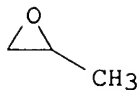


CM 3

CRN 697765-47-2
CMF (C3 H6 O . C2 H4 O) x
CCI PMS

CM 4

CRN 75-56-9
CMF C3 H6 O



CM 5

CRN 75-21-8
CMF C2 H4 O

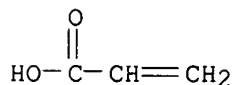


L91 ANSWER 2 OF 8 HCAPLUS COPYRIGHT 2006 ACS on STN
AN 2004:857543 HCAPLUS
DN 141:350828
TI Mixtures of at least two (meth)acrylates having at least two double bonds
for manufacture of hydrogels
IN Riegel, Ulrich; Daniel, Thomas; Hermeling, Dieter;
Elliott, Mark; Schwalm, Reinhold
PA BASF Aktiengesellschaft, Germany
SO PCT Int. Appl., 84 pp.
CODEN: PIXXD2
DT Patent
LA German
FAN.CNT 8

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
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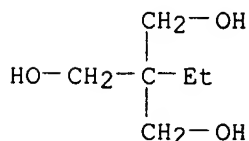
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	RW:	BW, GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZM, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM, AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IT, LU, MC, NL, PL, PT, RO, SE, SI, SK, TR, BF, BJ, CF, BG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG			
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	RW:	GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZM, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM, AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IT, LU, MC, NL, PT, RO, SE, SI, SK, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG			
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	DE 2003-10319462	A	20030429		
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DE 2002-10225943 A 20020611 <--
 WO 2004-EP3348 W 20040330
 OS MARPAT 141:350828
 AB Title mixts. for use as crosslinkers in the manufacture of superabsorbent hydrogels with high hydrolysis resistance and particle formation during manufacture have GFV 200-600 g/mol double bonds, with $GFV = \sum_{i=1}^n \alpha_i MW_i / Z_i$ [$\sum_{i=1}^n \alpha_i = 1$, α_i = mol fraction of compound (i) in the mixture, n [number of compds. in mixture] ≥ 2 , Z_i = number of double bonds in compound (i), MW_i = mol. weight of compound (i)]. A typical hydrogel was manufactured by radical polymerization of 220 g acrylic acid, 2201 g 37.3% aqueous Na acrylate solution, and 5.1 g mixture containing 69.3% 30:5 ethylene oxide-propylene oxide copolymer trimethylolpropane ether triacrylate and 30.7% Laromer TPGDA.
 IT **117989-76-1P**
 RL: IMF (Industrial manufacture); RCT (Reactant); PREP (Preparation); RACT (Reactant or reagent)
 (crosslinker; mixts. of at least two (meth)acrylates having at least two double bonds for crosslinkers for manufacture of hydrogels)
 RN 117989-76-1 HCAPLUS
 CN Oxirane, methyl-, polymer with oxirane, ether with 2-ethyl-2-(hydroxymethyl)-1,3-propanediol (3:1), tri-2-propenoate (9CI) (CA INDEX NAME)
 CM 1
 CRN 79-10-7
 CMF C3 H4 O2



CM 2

CRN 77-99-6
 CMF C6 H14 O3



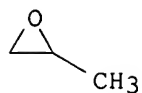
CM 3

CRN 9003-11-6
 CMF (C3 H6 O . C2 H4 O)x
 CCI PMS

CM 4

CRN 75-56-9

CMF C3 H6 O



CM 5

CRN 75-21-8

CMF C2 H4 O



IT 774577-40-1P, Acrylic acid-ethylene oxide-propylene oxide copolymer trimethylolpropane ether triacrylate-Laromer TPGDA-sodium acrylate copolymer 774577-49-0P, Acrylic acid-ethylene oxide-propylene oxide copolymer trimethylolpropane ether triacrylate-sodium acrylate copolymer 774577-55-8P, Acrylic acid-ethylene oxide-propylene oxide copolymer trimethylolpropane ether triacrylate-polyethylene glycol glycerol ether triacrylate-sodium acrylate copolymer 774577-77-4P, Acrylic acid-ethylene oxide-propylene oxide copolymer trimethylolpropane ether triacrylate-polyethylene glycol trimethylolpropane ether triacrylate-sodium acrylate copolymer 774580-94-8P, Acrylic acid-ethylene oxide-propylene oxide copolymer trimethylolpropane ether triacrylate-polypropylene glycol glycerol ether triacrylate-sodium acrylate copolymer
 RL: IMF (Industrial manufacture); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
 (mixts. of at least two (meth)acrylates having at least two double bonds for crosslinkers for manufacture of hydrogels)

RN 774577-40-1 HCAPLUS

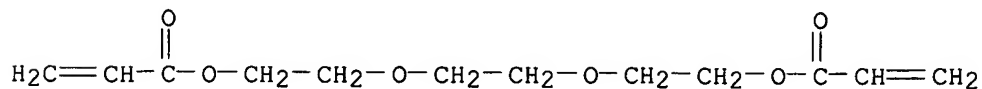
CN 2-Propenoic acid, polymer with (1-methyl-1,2-ethanediyl)bis[oxy(methyl-2,1-ethanediyl)] di-2-propenoate, methyloxirane polymer with oxirane ether with 2-ethyl-2-(hydroxymethyl)-1,3-propanediol (3:1) tri-2-propenoate, and sodium 2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 42978-66-5

CMF C15 H24 O6

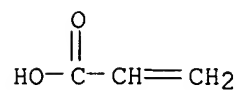
CCI IDS



3 (D1-Me)

CM 2

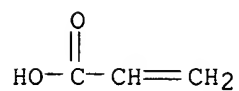
CRN 7446-81-3
CMF C3 H4 O2 . Na



● Na

CM 3

CRN 79-10-7
CMF C3 H4 O2

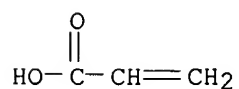


CM 4

CRN 117989-76-1
CMF C6 H14 O3 . 3 (C3 H6 O . C2 H4 O)x . 3 C3 H4 O2

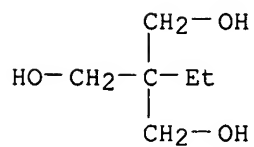
CM 5

CRN 79-10-7
CMF C3 H4 O2



CM 6

CRN 77-99-6
CMF C6 H14 O3

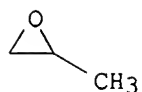


CM 7

CRN 9003-11-6
 CMF (C3 H6 O . C2 H4 O)x
 CCI PMS

CM 8

CRN 75-56-9
 CMF C3 H6 O



CM 9

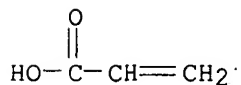
CRN 75-21-8
 CMF C2 H4 O



RN 774577-49-0 HCAPLUS
 CN 2-Propenoic acid, polymer with methyloxirane polymer with oxirane ether
 with 2-ethyl-2-(hydroxymethyl)-1,3-propanediol (3:1) tri-2-propenoate, and
 sodium 2-propenoate (9CI) (CA INDEX NAME)

CM 1

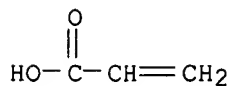
CRN 7446-81-3
 CMF C3 H4 O2 . Na



● Na

CM 2

CRN 79-10-7
 CMF C3 H4 O2

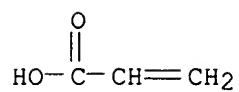


CM 3

CRN 117989-76-1
 CMF C6 H14 O3 . 3 (C3 H6 O . C2 H4 O)x . 3 C3 H4 O2

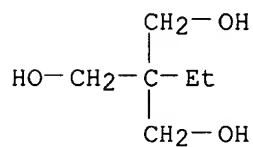
CM 4

CRN 79-10-7
 CMF C3 H4 O2



CM 5

CRN 77-99-6
 CMF C6 H14 O3

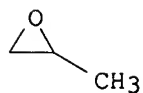


CM 6

CRN 9003-11-6
 CMF (C3 H6 O . C2 H4 O)x
 CCI PMS

CM 7

CRN 75-56-9
 CMF C3 H6 O



CM 8

CRN 75-21-8
 CMF C2 H4 O



RN 774577-55-8 HCAPLUS
 CN 2-Propenoic acid, polymer with methyloxirane polymer with oxirane ether

with 2-ethyl-2-(hydroxymethyl)-1,3-propanediol (3:1) tri-2-propenoate, $\alpha, \alpha', \alpha''$ -1,2,3-propanetriyltris[ω -(1-oxo-2-propenyl)oxy]poly(oxy-1,2-ethanediyl)] and sodium 2-propenoate (9CI) (CA INDEX NAME)

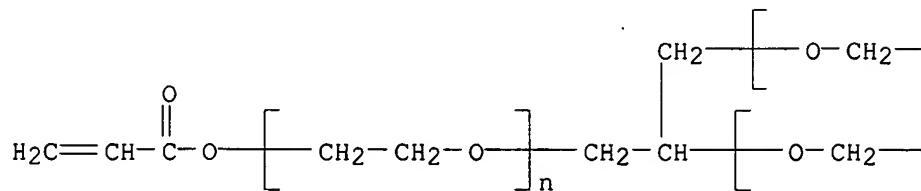
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CRN 101661-95-4

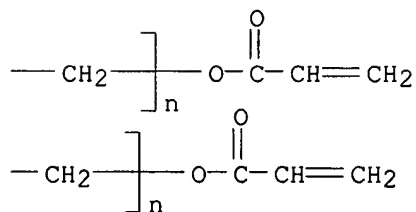
CMF (C2 H4 O)n (C2 H4 O)n (C2 H4 O)n C12 H14 O6

CCI PMS

PAGE 1-A



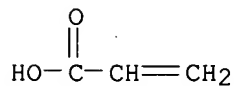
PAGE 1-B



CM 2

CRN 7446-81-3

CMF C3 H4 O2 . Na

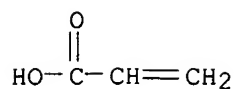


● Na

CM 3

CRN 79-10-7

CMF C3 H4 O2



CM 4

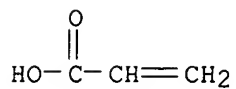
CRN 117989-76-1

CMF C6 H14 O3 . 3 (C3 H6 O . C2 H4 O)x . 3 C3 H4 O2

CM 5

CRN 79-10-7

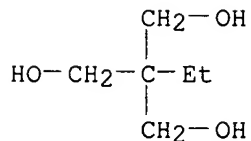
CMF C3 H4 O2



CM 6

CRN 77-99-6

CMF C6 H14 O3



CM 7

CRN 9003-11-6

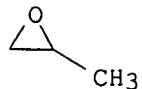
CMF (C3 H6 O . C2 H4 O)x

CCI PMS

CM 8

CRN 75-56-9

CMF C3 H6 O



CM 9

CRN 75-21-8

CMF C2 H4 O



RN 774577-77-4 HCAPLUS
 CN 2-Propenoic acid, polymer with α -hydro- ω -[(1-oxo-2-propenyl)oxy]poly(oxy-1,2-ethanediyl) ether with 2-ethyl-2-(hydroxymethyl)-1,3-propanediol (3:1), methyloxirane polymer with oxirane ether with 2-ethyl-2-(hydroxymethyl)-1,3-propanediol (3:1) tri-2-propenoate, and sodium 2-propenoate (9CI) (CA INDEX NAME)

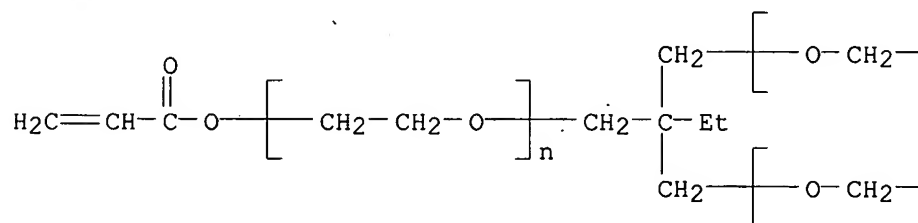
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CRN 28961-43-5

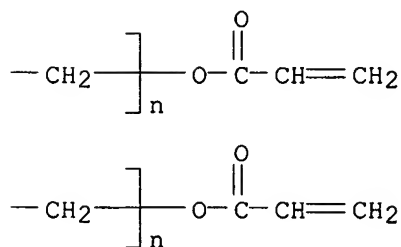
CMF (C2 H4 O)_n (C2 H4 O)_n (C2 H4 O)_n C15 H20 O6

CCI: PMS

PAGE 1-A



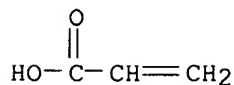
PAGE 1-B



CM 2

CRN 7446-81-3

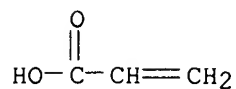
CMF C3 H4 O2 . Na



● Na

CM 3

CRN 79-10-7
CMF C3 H4 O2

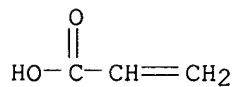


CM 4

CRN 117989-76-1
CMF C6 H14 O3 . 3 (C3 H6 O . C2 H4 O)x . 3 C3 H4 O2

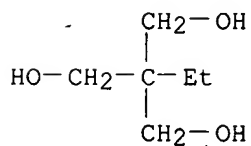
CM 5

CRN 79-10-7
CMF C3 H4 O2



CM 6

CRN 77-99-6
CMF C6 H14 O3

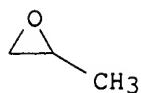


CM 7

CRN 9003-11-6
CMF (C3 H6 O . C2 H4 O)x
CCI PMS

CM 8

CRN 75-56-9
CMF C3 H6 O



CM 9

CRN 75-21-8

CMF C2 H4 O



RN 774580-94-8 HCAPLUS

CN 2-Propenoic acid, polymer with methyloxirane polymer with oxirane ether with 2-ethyl-2-(hydroxymethyl)-1,3-propanediol (3:1) tri-2-propenoate, $\alpha, \alpha', \alpha''$ -1,2,3-propanetriyltris[ω -[(1-oxo-2-propenyl)oxy]poly[oxy(methyl-1,2-ethanediyl)]] and sodium 2-propenoate (9CI) (CA INDEX NAME)

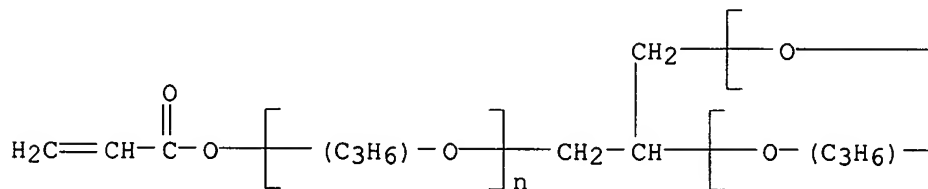
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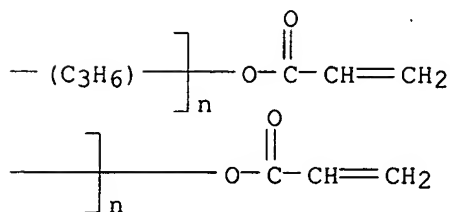
CMF (C3 H6 O)_n (C3 H6 O)_n (C3 H6 O)_n C12 H14 O6

CCI IDS, PMS

PAGE 1-A



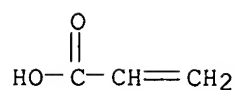
PAGE 1-B



CM 2

CRN 7446-81-3

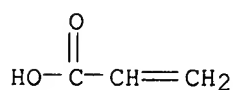
CMF C3 H4 O2 . Na



● Na

CM 3

CRN 79-10-7
CMF C3 H4 O2

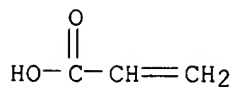


CM 4

CRN 117989-76-1
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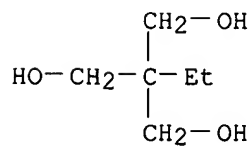
CM 5

CRN 79-10-7
CMF C3 H4 O2



CM 6

CRN 77-99-6
CMF C6 H14 O3



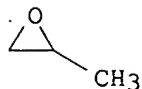
CM 7

CRN 9003-11-6
CMF (C3 H6 O . C2 H4 O)x
CCI PMS

CM 8

CRN 75-56-9

CMF C3 H6 O



CM 9

CRN 75-21-8

CMF C2 H4 O

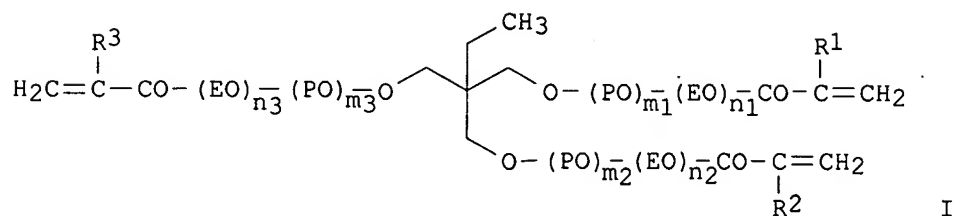


L91 ANSWER 3 OF 8 HCAPLUS COPYRIGHT 2006 ACS on STN
 AN 2003:991565 HCAPLUS
 DN 140:43143
 TI Acrylic esters of alkoxyated trimethylolpropane useful in production of hydrogels
 IN Popp, Andreas; Daniel, Thomas; Schroeder, Juergen; Jaworek, Thomas; Funk, Ruediger; Schwalm, Reinhold; Weismantel, Matthias; Riegel, Ulrich
 PA BASF Aktiengesellschaft, Germany
 SO PCT Int. Appl., 65 pp.
 CODEN: PIXXD2
 DT Patent
 LA German
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WO 2003-EP6028	A	20030610		
WO 2003-EP6054	W	20030610		
DE 2003-10358372	A	20031211		
WO 2004-EP3348	W	20040330		

GI



AB Acrylic and/or methacrylic esters of alkoxyated trimethylolpropane have the general formula (I), where EO is -OCH₂CH₂-, PO independently represents -OCH₂CH(CH₃)- or -OCH(CH₃)CH₂-; n₁, n₂, n₃ are independently 4, 5 or 6; the total of n₁, n₂ and n₃ equals to 14, 15 or 16; m₁, m₂, m₃ are independently 1, 2 or 3; the total of m₁, m₂ and m₃ equals to 4, 5 or 6; and R₁, R₂ and R₃ are independently H or CH₃. The esters can be used as crosslinking agents in production of hydrogels, or as components in cement additive compns. or in production of polymer dispersions and lacquers. Thus, an alkoxyated trimethylolpropane was produced by reacting trimethylolpropane (77) in water in the presence of KOH (0.5) with propylene oxide (167) at 120-130°, followed by adding and reacting with ethylene oxide (379 g) at 145-155°. The alkoxyated trimethylolpropane (887) was mixed with acrylic acid (216) and esterified in the presence of H₂SO₄ (5 parts) and polymerization inhibitors. The obtained alkoxyated trimethylolpropane triacrylate was used as a crosslinking agent in radical polymerization with acrylic acid and sodium acrylate.

IT 150604-34-5P

RL: IMF (Industrial manufacture); PREP (Preparation)
(acrylic esters of alkoxyated trimethylolpropane useful in production of hydrogels)

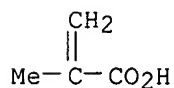
RN 150604-34-5 HCAPLUS

CN Oxirane, methyl-, polymer with oxirane, ether with 2-ethyl-2-(hydroxymethyl)-1,3-propanediol (3:1), tris(2-methyl-2-propenoate), block (9CI) (CA INDEX NAME)

CM 1

CRN 79-41-4

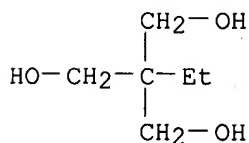
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CM 2

CRN 77-99-6

CMF C6 H14 O3



CM 3

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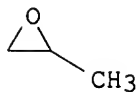
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CCI PMS

CM 4

CRN 75-56-9

CMF C3 H6 O



CM 5

CRN 75-21-8

CMF C2 H4 O



IT 633314-15-5P

RL: IMF (Industrial manufacture); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(acrylic esters of alkoxyated trimethylolpropane useful in production of hydrogels)

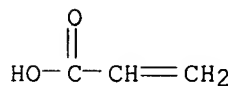
RN 633314-15-5 HCAPLUS

CN 2-Propenoic acid, polymer with methyloxirane block polymer with oxirane ether with 2-ethyl-2-(hydroxymethyl)-1,3-propanediol (3:1) tri-2-propenoate, and sodium 2-propenoate (9CI) (CA INDEX NAME)

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CRN 7446-81-3

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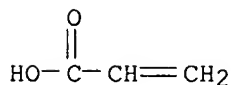


● Na

CM 2

CRN 79-10-7

CMF C3 H4 O2



CM 3

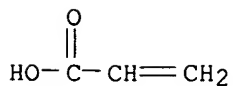
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CM 4

CRN 79-10-7

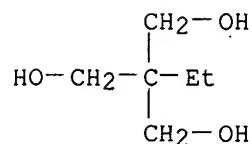
CMF C3 H4 O2



CM 5

CRN 77-99-6

CMF C6 H14 O3



CM 6

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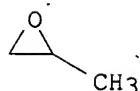
CMF (C3 H6 O . C2 H4 O) x

CCI PMS

CM 7

CRN 75-56-9

CMF C3 H6 O



CM 8

CRN 75-21-8

CMF C2 H4 O



IT 633314-14-4P

RL: IMF (Industrial manufacture); RCT (Reactant); PREP (Preparation); RACT (Reactant or reagent)

(acrylic esters of alkoxylated trimethylolpropane useful in production of hydrogels)

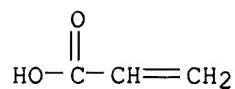
RN 633314-14-4 HCAPLUS

CN Oxirane, methyl-, polymer with oxirane, ether with 2-ethyl-2-(hydroxymethyl)-1,3-propanediol (3:1), tri-2-propenoate, block (9CI) (CA INDEX NAME)

CM 1

CRN 79-10-7

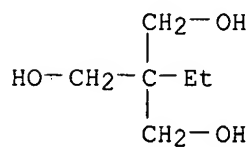
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CRN 77-99-6

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CRN 106392-12-5

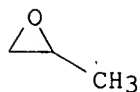
CMF (C3 H6 O . C2 H4 O)x

CCI PMS

CM 4

CRN 75-56-9

CMF C3 H6 O



CM 5

CRN 75-21-8

CMF C2 H4 O



RETABLE

Referenced Author (RAU)	Year (RPY)	VOL (RVL)	PG (RPG)	Referenced Work (RWK)	Referenced File
Basf Corp	2001			WO 0156625 A	HCAPLUS
Christensen, S	2001			WO 0145758 A	HCAPLUS
Gartner, H	1996			US 5506324 A	HCAPLUS
Kushi, K	1994			US 5356754 A	HCAPLUS

L91 ANSWER 4 OF 8 HCAPLUS COPYRIGHT 2006 ACS on STN
 AN 2003:991563 HCAPLUS

DN 140:28395
 TI Acrylic esters of alkoxyated trimethylolpropane useful in production of hydrogels
 IN Popp, Andreas; Daniel, Thomas; Schroeder, Juergen; Jaworek, Thomas; Funk, Ruediger; Schwalm, Reinhold; Weismantel, Matthias; Riegel, Ulrich
 PA BASF Aktiengesellschaft, Germany
 SO PCT Int. Appl., 70 pp.
 CODEN: PIXXD2
 DT Patent
 LA German
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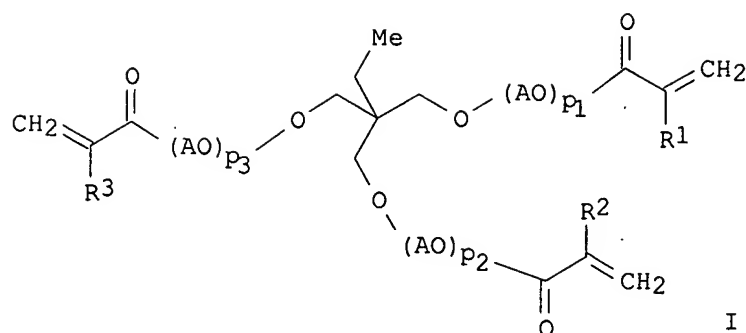
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 SN, TD, TG

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 WO 2004-EP3348 W 20040330
 WO 2004-EP3551 W 20040402
 WO 2004-EP6033 W 20040604

GI



AB Acrylic and/or methacrylic esters of alkoxyated trimethylolpropane have the general formula (I), where each AO independently represents EO, PO or BO, EO being $-\text{OCH}_2\text{CH}_2-$, PO being $-\text{OCH}_2\text{CH}(\text{CH}_3)-$ or $-\text{OCH}(\text{CH}_3)\text{CH}_2-$, BO being $-\text{OCH}_2\text{CH}(\text{CH}_2\text{CH}_3)-$ or $-\text{OCH}(\text{CH}_2\text{CH}_3)\text{CH}_2-$; the total of p_1 , p_2 and p_3 equals to an integer from 28 to 75; and R_1 , R_2 and R_3 are independently H or CH_3 . The esters can be used as crosslinking agents in production of hydrogels, or as components in cement additive compns. or in production of polymer dispersions and lacquers. Thus, an alkoxyated trimethylolpropane was produced by reacting trimethylolpropane (77) in water in the presence of KOH (0.5) with ethylene oxide (759) at $145-155^\circ$, followed by adding and reacting with propylene oxide (167 g) at $120-130^\circ$. The alkoxyated trimethylolpropane (1,427) was mixed with acrylic acid (216) and esterified in the presence of H_2SO_4 (5 parts) and polymerization inhibitors.

The obtained alkoxyated trimethylolpropane triacrylate was used as a crosslinking agent in radical polymerization with acrylic acid and sodium acrylate.

IT 150604-34-5P

RL: IMF (Industrial manufacture); PREP (Preparation)

(acrylic esters of alkoxyated trimethylolpropane useful in production of hydrogels)

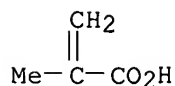
RN 150604-34-5 HCAPLUS

CN Oxirane, methyl-, polymer with oxirane, ether with 2-ethyl-2-(hydroxymethyl)-1,3-propanediol (3:1), tris(2-methyl-2-propenoate), block (9CI) (CA INDEX NAME)

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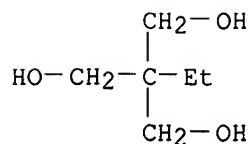
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CM 2

CRN 77-99-6

CMF C6 H14 O3



CM 3

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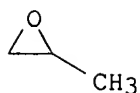
CMF (C3 H6 O . C2 H4 O) x

CCI PMS

CM 4

CRN 75-56-9

CMF C3 H6 O



CM 5

CRN 75-21-8

CMF C2 H4 O



IT 633314-15-5P

RL: IMF (Industrial manufacture); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

(acrylic esters of alkoxylated trimethylolpropane useful in production of hydrogels)

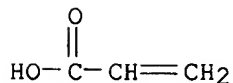
RN 633314-15-5 HCAPLUS

CN 2-Propenoic acid, polymer with methyloxirane block polymer with oxirane ether with 2-ethyl-2-(hydroxymethyl)-1,3-propanediol (3:1) tri-2-propenoate, and sodium 2-propenoate (9CI) (CA INDEX NAME)

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CRN 7446-81-3

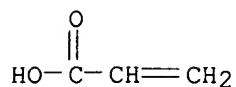
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● Na

CM 2

CRN 79-10-7
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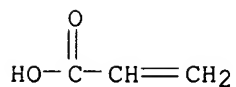


CM 3

CRN 633314-14-4
CMF C6 H14 O3 . 3 (C3 H6 O . C2 H4 O)x . 3 C3 H4 O2

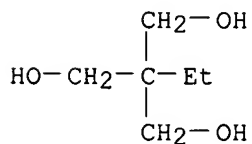
CM 4

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CM 5

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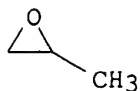


CM 6

CRN 106392-12-5
CMF (C3 H6 O . C2 H4 O)x
CCI PMS

CM 7

CRN 75-56-9
CMF C3 H6 O



CM 8

CRN 75-21-8

CMF C2 H4 O



IT 633314-14-4P

RL: IMF (Industrial manufacture); RCT (Reactant); PREP (Preparation); RACT (Reactant or reagent)

(acrylic esters of alkoxyated trimethylolpropane useful in production of hydrogels)

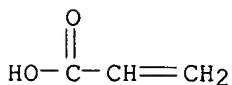
RN 633314-14-4 HCAPLUS

CN Oxirane, methyl-, polymer with oxirane, ether with 2-ethyl-2-(hydroxymethyl)-1,3-propanediol (3:1), tri-2-propenoate, block (9CI) (CA INDEX NAME)

CM 1

CRN 79-10-7

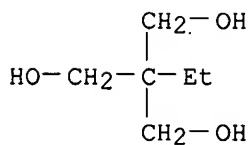
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CM 2

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CM 3

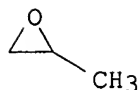
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CMF (C3 H6 O . C2 H4 O)x

CCI PMS

CM 4

CRN 75-56-9
CMF C3 H6 O



CM 5

CRN 75-21-8
CMF C2 H4 O



RETABLE

Referenced Author (RAU)	Year (RPY)	VOL (RVL)	PG (RPG)	Referenced Work (RWK)	Referenced File
Abraham, B	1968			US 3380831 A	
Basf Ag	1988			EP 0264841 A	HCAPLUS
Dai Ichi Kogyo Seiyaku	1999			EP 0923147 A	HCAPLUS
Gartner, H	1996			US 5506324 A	HCAPLUS
Hartmann, H	1997			US 5661220 A	HCAPLUS
Kushi, K	1994			US 5356754 A	HCAPLUS
Matsushita Electric Ind	1997			EP 0777287 A	HCAPLUS
Ritter, W	1997			US 5648518 A	HCAPLUS

L91 ANSWER 5 OF 8 HCAPLUS COPYRIGHT 2006 ACS on STN

AN 2003:991562 HCAPLUS

DN 140:43131

TI Production of crosslinked hydrogels using esters of polyalcohols and unsaturated carboxylic acids

IN Jaworek, Thomas; Daniel, Thomas; Wolf, Lothar;

Koeniger, Rainer; Schwalm, Reinhold; Hartmann, Gabriele; Wickel, Stefan

PA BASF Aktiengesellschaft, Germany

SO PCT Int. Appl., 85 pp.

CODEN: PIXXD2

DT Patent

LA German

FAN.CNT 8

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	WO 2003104299	A1	20031218	WO 2003-EP5940	20030606 <--
	W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NI, NO, NZ, OM, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW				
	RW: GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZM, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM, AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IT, LU, MC, NL, PT, RO, SE, SI, SK, TR,				

BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG

DE 10225943	A1	20040108	DE 2002-10225943	20020611 <--
AU 2003242636	A1	20031222	AU 2003-242636	20030606 <--
BR 2003011500	A	20050308	BR 2003-11500	20030606 <--
EP 1516010	A1	20050323	EP 2003-757035	20030606 <--
R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, SK				
US 2005176910	A1	20050811	US 2003-514569	20030606 <--
CN 1659212	A	20050824	CN 2003-813666	20030606 <--
JP 2005533875	T2	20051110	JP 2004-511365	20030606 <--
PRAI, DE 2002-10225943	A	20020611	<--	
WO 2003-EP5940	W	20030606		

OS MARPAT 140:43131

AB A crosslinked hydrogel is produced by a process comprising the steps of
(a) reacting a polyalc. A with at least one ethylenically unsatd.
carboxylic acid B in the presence of an esterification catalyst C, at
least one polymerization inhibitor D and, optionally, a solvent E forming an
azeotrope with water under conditions of synthesis of an ester F, (b)
optionally, removing at least a part of water from the reaction mixture
during and/or after the step (a), (c) optionally, neutralizing the
reaction mixture, (d) removing the optional azeotrope-forming solvent by
distillation, (e) stripping the reaction mixture with an inert gas, (f)
polymerizing
the reaction mixture with optional monoethylenically unsatd. compds. N and
at least one other hydrophilic monomer M in the presence of a radical
initiator K and, optionally, a graftable substrate L, (g) optionally,
crosslinking the polymerized mixture, (h) drying the polymer, and (i)
optionally, grinding and/or sieving the polymer. Thus, ethoxylated
trimethylolpropane (Polyol TP 70) (681) was mixed with acrylic acid (414)
and esterified in methylcyclohexane (365) in the presence of H₂SO₄ (5
parts) and polymerization inhibitors with distilling off 102 parts of water
formed
during the reaction. The ethoxylated trimethylolpropane triacrylate was
used as a crosslinking agent in polymerization with acrylic acid and sodium
acrylate.

IT **634615-81-9P**
RL: IMF (Industrial manufacture); PRP (Properties); TEM (Technical or
engineered material use); PREP (Preparation); USES (Uses)
(production of crosslinked hydrogels using esters of polyalcs. and unsatd.
carboxylic acids)

RN 634615-81-9 . HCAPLUS

CN 2-Propenoic acid, polymer with 2,2'-[1,2-ethanediylbis(oxyethylene)]bis[o
xirane], α -hydro- ω -[(1-oxo-2-propenyl)oxy]poly(oxy-1,2-
ethanediyl) ether with 2-ethyl-2-(hydroxymethyl)-1,3-propanediol (3:1),
1,2-propanediol and sodium 2-propenoate (9CI) (CA INDEX NAME)

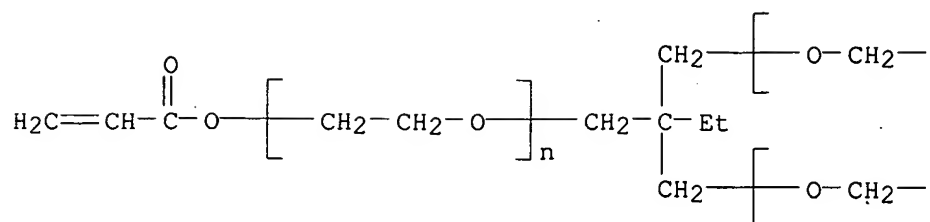
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CRN 28961-43-5

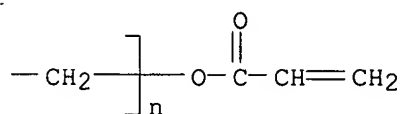
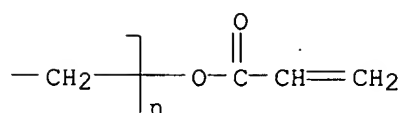
CMF (C₂ H₄ O)_n (C₂ H₄ O)_n (C₂ H₄ O)_n C₁₅ H₂₀ O₆

CCI PMS

PAGE 1-A



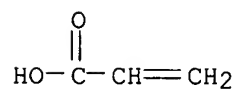
PAGE 1-B



CM 2

CRN 7446-81-3

CMF C3 H4 O2 . Na

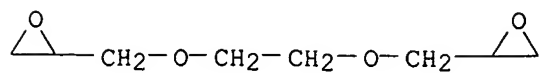


● Na

CM 3

CRN 2224-15-9

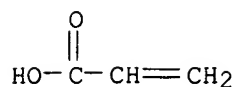
CMF C8 H14 O4



CM 4

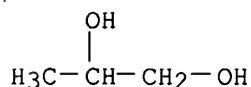
CRN 79-10-7

CMF C3 H4 O2



CM 5

CRN 57-55-6
CMF C3 H8 O2



RETABLE

Referenced Author (RAU)	Year (RPY)	VOL (RVL)	PG (RPG)	Referenced Work (RWK)	Referenced File
Basf Ag	1998			EP 0874014 A	HCAPLUS
Basf Corp	2001			WO 0156625 A	HCAPLUS
Beck, E	1998			US 5821383 A	HCAPLUS
Dow Chemical Co	1993			WO 9321237 A	HCAPLUS
Dow Chemical Co	2001			WO 0141818 A	HCAPLUS
Hoechst Celanese Corp	1989			EP 0331845 A	HCAPLUS
Ritter, W	1994			US 5350877 A	HCAPLUS
Speitkamp, L	1993			US 5198574 A	HCAPLUS
Stockhausen Chem Fab Gm	1998			WO 9847951 A	HCAPLUS

L91 ANSWER 6 OF 8 HCAPLUS COPYRIGHT 2006 ACS on STN

AN 2000:127557 HCAPLUS

DN 132:152313

TI Extraction procedure for the production of pure esters of
α,β-ethylenically unsaturated carboxylic acids

IN Paulus, Wolfgang; Bernhard, Ludwig; Johansson, Astrid Carina; Haas,
Guenter; Geisendoerfer, Matthias; Beck, Erich; Leube, Hartmann; Kuse,
Reinhold; Jaeger, Ulrich

PA **BASF A.-G., Germany**

SO Ger. Offen., 10 pp.

CODEN: GWXXBX

DT Patent

LA German

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	DE 19836788	A1	20000224	DE 1998-19836788	19980813 <--
	DE 19836788	B4	20060928		
PRAI	DE 1998-19836788		19980813	<--	

AB A procedure for the production of pure, water-insol. esters of
α,β-ethylenically unsatd. carboxylic acids (e.g., acrylic acid
esters of ethoxylated propoxylated trimethylolpropane) from its mixts.
which are contaminated with unconverted carboxylic acid(s) and/or acid
group-containing catalysts comprises: (A) conducting a liquid-liquid
extraction against
an aqueous phase containing the esters using a base; and (B) the aqueous base
with the
impurities contained in it are phase separated

IT 117989-76-1P

RL: PUR (Purification or recovery); PREP (Preparation)

(extraction procedure for the production of pure esters of ethylenically unsatd.

carboxylic acids)

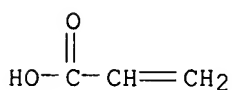
RN 117989-76-1 HCAPLUS

CN Oxirane, methyl-, polymer with oxirane, ether with 2-ethyl-2-(hydroxymethyl)-1,3-propanediol (3:1), tri-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 79-10-7

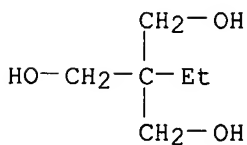
CMF C3 H4 O2



CM 2

CRN 77-99-6

CMF C6 H14 O3



CM 3

CRN 9003-11-6

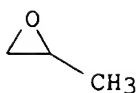
CMF (C3 H6 O . C2 H4 O) x

CCI PMS

CM 4

CRN 75-56-9

CMF C3 H6 O



CM 5

CRN 75-21-8

CMF C2 H4 O



RETABLE

Referenced Author (RAU)	Year (RPY)	VOL (RVL)	PG (RPG)	Referenced Work (RWK)	Referenced File
Anon				EP 0618187 A1	HCAPLUS
Anon				JP 62106052 A	HCAPLUS
Anon				JP 62106056 A	HCAPLUS
Anon				JP 62106057 A	HCAPLUS
Anon				JP 63174951 A	HCAPLUS
Anon				JP 63275544 A	HCAPLUS
Ullmann	1985	A1	168	Encyclopedia of Indu	

L91 ANSWER 7 OF 8 HCAPLUS COPYRIGHT 2006 ACS on STN

AN 1989:10884 HCAPLUS

DN 110:10884

TI Copolymers from hydrophobic (meth)acrylic acid esters and hydrophilic monomers, method of their preparation, and application as petroleum emulsion breaker

IN Barthold, Klaus; Baur, Richard; Crema, Stefano Carlo; Lasowski, Juergen; Oppenlaender, Knut; Heide, Wilfried

PA BASF A.-G., Fed. Rep. Ger.

SO Ger. Offen., 16 pp.

CODEN: GWXXBX

DT Patent

LA German

FAN.CNT 2

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	DE 3635489	A1	19880421	DE 1986-3635489	19861018 <--
	NO 8704319	A	19880419	NO 1987-4319	19871016 <--
	NO 171682	B	19930111		
	NO 171682	C	19930421		
	EP 264841	A2	19880427	EP 1987-115126	19871016 <--
	EP 264841	A3	19890712		
	EP 264841	B1	19921230		
	R: DE, FR, GB, IT, NL				
	CA 1309552	A1	19921027	CA 1987-549642	19871019 <--
	US 5472617	A	19951205	US 1993-175935	19931227 <--
PRAI	DE 1986-3635489	A	19861018	<--	
	US 1992-905130	B2	19920624	<--	

AB The copolymers useful as petroleum emulsion breakers are prepared from hydrophobic (meth)acrylic acid esters, their alc. components derived from a mixture of polyglycols and polyglycol ethers, with hydrophilic, ethylenic unsatd. monomers, whereby in copolymers (i) all or substantially all free OH-groups are etherified, esterified, or converted into urethane groups and/or (ii) by esterification the acid is neutralized by amine addition. Thus, 893 g acrylic acid ester with ethoxylated-propoxylated trimethylolpropane and 95.8 g acrylic acid, in the presence of 453 mg 2,2'-azobisisobutyronitrile and 460 g xylene, were copolymerized at 80° for 3 h to obtain a polymer (K-value 13.2, measured as 1% xylene solution), which was then treated with 14.3 g acetic anhydride at 100° for 3 h for end group protection and neutralized with 7.7 g tributylamine for catalytic acid to yield a final product having 23.8 K-value and <1 OH-number.

IT 115165-81-6D, polymers with (meth)acrylates 117801-94-2

117801-95-3 117801-97-5

RL: USES (Uses)

(petroleum emulsion breaker)

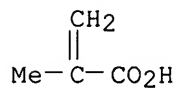
RN 115165-81-6 HCAPLUS

CN Oxirane, methyl-, polymer with oxirane, ether with 2-ethyl-2-(hydroxymethyl)-1,3-propanediol (3:1), 2-methyl-2-propenoate, block (9CI)
(CA INDEX NAME)

CM 1

CRN 79-41-4

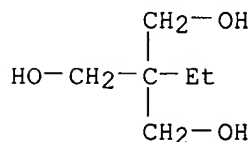
CMF C4 H6 O2



CM 2

CRN 77-99-6

CMF C6 H14 O3



CM 3

CRN 106392-12-5

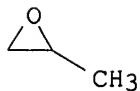
CMF (C3 H6 O . C2 H4 O) x

CCI PMS

CM 4

CRN 75-56-9

CMF C3 H6 O



CM 5

CRN 75-21-8

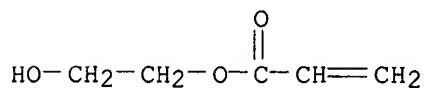
CMF C2 H4 O



RN 117801-94-2 HCAPLUS
 CN 2-Propenoic acid, polymer with 2-hydroxyethyl 2-propenoate and
 methyloxirane block polymer with oxirane ether with 2-ethyl-2-
 (hydroxymethyl)-1,3-propanediol (3:1) 2-propenoate (9CI) (CA INDEX NAME)

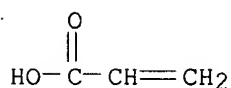
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CRN 818-61-1
 CMF C5 H8 O3



CM 2

CRN 79-10-7
 CMF C3 H4 O2

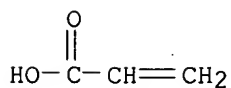


CM 3

CRN 117742-99-1
 CMF C6 H14 O3 . 3 (C3 H6 O . C2 H4 O)x . x C3 H4 O2

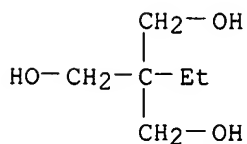
CM 4

CRN 79-10-7
 CMF C3 H4 O2



CM 5

CRN 77-99-6
 CMF C6 H14 O3



CM 6

CRN 106392-12-5

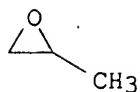
CMF (C3 H6 O . C2 H4 O)x

CCI PMS

CM 7

CRN 75-56-9

CMF C3 H6 O



CM 8

CRN 75-21-8

CMF C2 H4 O



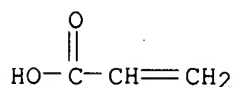
RN 117801-95-3 HCAPLUS

CN 2-Propenoic acid, polymer with methyloxirane block polymer with oxirane ether with 2-ethyl-2-(hydroxymethyl)-1,3-propanediol (3:1) 2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 79-10-7

CMF C3 H4 O2



CM 2

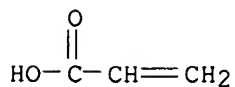
CRN 117742-99-1

CMF C6 H14 O3 . 3 (C3 H6 O . C2 H4 O)x . x C3 H4 O2

CM 3

CRN 79-10-7

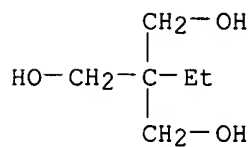
CMF C3 H4 O2



CM 4

CRN 77-99-6

CMF C6 H14 O3



CM 5

CRN 106392-12-5

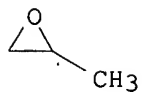
CMF (C3 H6 O . C2 H4 O)x

CCI PMS

CM 6

CRN 75-56-9

CMF C3 H6 O



CM 7

CRN 75-21-8

CMF C2 H4 O



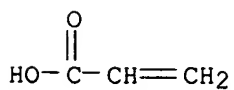
RN 117801-97-5 HCAPLUS

CN 2-Propenoic acid, polymer with ethyloxirane block polymer with methyloxirane and oxirane ether with 2-ethyl-2-(hydroxymethyl)-1,3-propanediol (3:1) 2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 79-10-7

CMF C3 H4 O2



CM 2

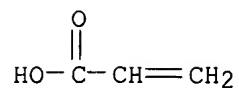
CRN 117742-97-9

CMF C6 H14 O3 . 3 (C4 H8 O . C3 H6 O . C2 H4 O)x . x C3 H4 O2

CM 3

CRN 79-10-7

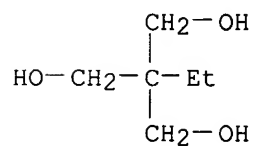
CMF C3 H4 O2



CM 4

CRN 77-99-6

CMF C6 H14 O3



CM 5

CRN 166089-41-4

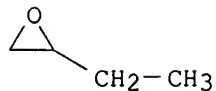
CMF (C4 H8 O . C3 H6 O . C2 H4 O)x

CCI PMS

CM 6

CRN 106-88-7

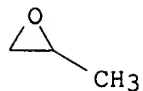
CMF C4 H8 O



CM 7

CRN 75-56-9

CMF C3 H6 O



CM 8

CRN 75-21-8

CMF C2 H4 O



L91 ANSWER 8 OF 8 HCAPLUS COPYRIGHT 2006 ACS on STN

AN 1989:9783 HCAPLUS

DN 110:9783

TI Acrylate-amine adducts for radiation-curable compositions

IN Weiss, Wolfram; Beck, Erich; Jacobi, Manfred; Richter, Peter

PA BASF A.-G., Fed. Rep. Ger.

SO Ger. Offen., 6 pp.

CODEN: GWXXBX

DT Patent

LA German

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	DE 3706355	A1	19880908	DE 1987-3706355	19870227 <--
	JP 63227553	A2	19880921	JP 1988-35424	19880219 <--
	EP 280222	A2	19880831	EP 1988-102525	19880220 <--
	EP 280222	A3	19900704		

R: AT, BE, CH, DE, ES, FR, GB, IT, LI, LU, NL, SE

PRAI DE 1987-3706355 A 19870227 <--

AB Addition products of a primary monoamine and an ester of (meth)acrylic acid and a polyhydric alc. (0.05-0.4 mol NH₂/mol double bonds) have good storage stability, cure quickly and completely during irradiation in air, and are useful in coatings and printing inks. Ethanolamine 61, tripropylene glycol diacrylate 840, and BHT 0.9 g were heated at 60° to give a clear, colorless product having viscosity 130 mPa-s (at 23°) before and after 6 wk of storage at 60° in the dark. A mixture of the product 100, Ph₂CO 2, and benzil di-Me ketal 1 g was coated (100 μm) on glass and cured in UV light.

IT 117989-76-1DP, addition products with primary amines

RL: PREP (Preparation)

(preparation of storage-stable, photocurable)

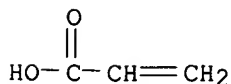
RN 117989-76-1 HCAPLUS

CN Oxirane, methyl-, polymer with oxirane, ether with 2-ethyl-2-(hydroxymethyl)-1,3-propanediol (3:1), tri-2-propenoate (9CI) (CA INDEX NAME)

CM 1

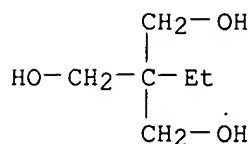
CRN 79-10-7

CMF C3 H4 O2



CM 2

CRN 77-99-6
 CMF C6 H14 O3

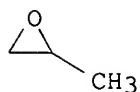


CM 3

CRN 9003-11-6
 CMF (C3 H6 O . C2 H4 O)x
 CCI PMS

CM 4

CRN 75-56-9
 CMF C3 H6 O



CM 5

CRN 75-21-8
 CMF C2 H4 O



=> d 190 bib abs hitstr retable tot

L90 ANSWER 1 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN
 AN 2005:23717 HCAPLUS
 DN 143:348711
 TI Study on UV-curable coatings for compact disk
 AU Guo, Jinbao; Du, Juan; Wei, Jie
 CS College of Material Science and Engineering, Beijing University of
 Chemical Technology, Beijing, 100029, Peop. Rep. China
 SO Tuliao Gongye (2003), 33(12), 1-4
 CODEN: TLKYD5; ISSN: 0253-4312
 PB Huagongbu Tuliao Gongye Yanjiuso
 DT Journal
 LA Chinese
 AB The relation of the performance of UV-curable coatings with active

IT 866003-83-0P

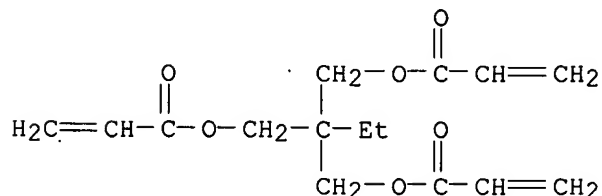
RN 866003-83-0 HCAPLUS

CM 1

CCI IDS, PMS

$$\text{H}_2\text{C}=\text{CH}-\overset{\text{O}}{\parallel}{\text{C}}-\text{O}-\left[(\text{C}_3\text{H}_6)-\text{O} \right]_n-\text{CH}_2-\text{CH}_2-\text{O}-\text{CH}_2-\text{CH}_2-\text{O}-\text{CH}_2-$$
$$-\text{CH}_2-\left[\text{O}-(\text{C}_3\text{H}_6)-\text{O}-\overset{\overset{\text{O}}{\parallel}}{\text{C}}-\text{CH}=\text{CH}_2 \right]_n$$

CMF C15 H20 O6



jan delaval - 16 november 2006

TI Photosensitive polymer compositions with good plating resistance and strippability and photosensitive elements containing them

IN Sawabe, Masaru; Ishimaru, Toshiaki

PA Hitachi Chemical Co., Ltd., Japan

SO Jpn. Kokai Tokkyo Koho, 13 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 2

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2004004635	A2	20040108	JP 2003-78279	20030320 <--
	JP 3795872	B2	20060712		
	JP 2002328469	A2	20021115	JP 2002-18913	19930215 <--
	JP 3437179	B2	20030818		
PRAI	JP 2002-18913	A3	19930215	<--	
	JP 1993-25691	A3	19930215	<--	

AB The compns., useful as plating resists for printed circuit boards, contain ethylenically unsatd. compds. having ≥ 3 unsatd. groups $\text{CH}_2:\text{CR}_1\text{CO}(\text{OR}_2)_m(\text{OR}_3)_n\text{O}$ ($\text{R}_1 = \text{H, Me}$; $\text{R}_2, \text{R}_3 = \text{ethylene, propylene}$; $\text{R}_2 \neq \text{R}_3$; $m, n \geq 1$). The photosensitive elements have the photosensitive polymer composition layers on support films.

IT 117989-76-1 161278-82-6

RL: TEM (Technical or engineered material use); USES (Uses)
(photosensitive polymer compns. containing ethoxy- and propoxy-containing unsatd. compds. with good strippability for plating resists)

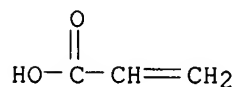
RN 117989-76-1 HCAPLUS

CN Oxirane, methyl-, polymer with oxirane, ether with 2-ethyl-2-(hydroxymethyl)-1,3-propanediol (3:1), tri-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 79-10-7

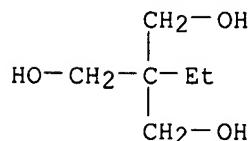
CMF C3 H4 O2



CM 2

CRN 77-99-6

CMF C6 H14 O3



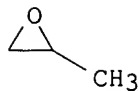
CM 3

CRN 9003-11-6

CMF (C3 H6 O . C2 H4 O)x
CCI PMS

CM 4

CRN 75-56-9
CMF C3 H6 O



CM 5

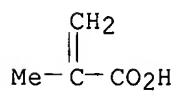
CRN 75-21-8
CMF C2 H4 O



RN 161278-82-6 HCAPLUS
CN Oxirane, methyl-, polymer with oxirane, ether with 2-ethyl-2-(hydroxymethyl)-1,3-propanediol (3:1), tris(2-methyl-2-propenoate) (9CI)
(CA INDEX NAME)

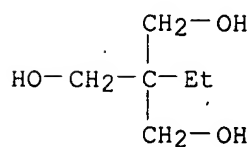
CM 1

CRN 79-41-4
CMF C4 H6 O2



CM 2

CRN 77-99-6
CMF C6 H14 O3



CM 3

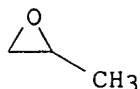
CRN 9003-11-6
CMF (C3 H6 O . C2 H4 O)x

CCI PMS

CM 4

CRN 75-56-9

CMF C3 H6 O



CM 5

CRN 75-21-8

CMF C2 H4 O



L90 ANSWER 3 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN
 AN 2003:470688 HCAPLUS
 DN 139:38047
 TI UV-curable coating compositions for protecting optical recording media and the protected media
 IN Shoji, Toshihiro
 PA Dainippon Ink and Chemicals, Inc., Japan
 SO Jpn. Kokai Tokkyo Koho, 8 pp.
 CODEN: JKXXAF
 DT Patent
 LA Japanese
 FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2003171620	A2	20030620	JP 2001-374143	20011207 <--
PRAI	JP 2001-374143		20011207 <--		

AB Optical recording media bearing recording bits, Ag or its metal alloy such as compact disks are protected by a coating layer which has a 1% MeOH solution pH of 4.5-6.8 and contains 4-benzoyl-4'-methyldiphenyl sulfide as photoinitiator for reducing block error rate. Thus, coating a mixture of trimethylolpropane triacrylate 35, ETA 300 (ethoxylated trimethylolpropane triacrylate) 30, APG 200 (tripropylene glycol diacrylate) 26, 2-hydroxyethyl methacrylate 5, benzophenone 3, 5.7% 4-benzoyl-4'-methyldiphenyl sulfide 6 and Megafac F 173 (fluoro surfactant) 0.2 parts on the surface of a polycarbonate disk substrate bearing a precoated 200-nm phthalocyanine colorant layer and a 80-nm sputtered Ag layer to a thickness of 7 μm and irradiating with UV light at 500 mJ/cm² gave a protective coating with reduced block error rate.

IT **540469-43-0P**, ETA 300-2-hydroxyethyl methacrylate-NK Ester APG 200-trimethylolpropane triacrylate copolymer
 RL: IMF (Industrial manufacture); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
 (UV-curable coating compns. for protecting optical disks with low block error rate)

RN 540469-43-0 HCAPLUS

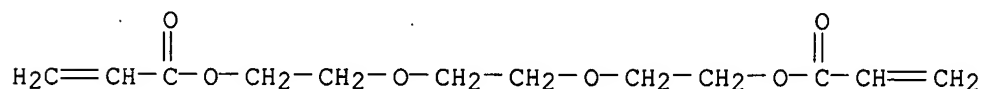
CN 2-Propenoic acid, 2-methyl-, 2-hydroxyethyl ester, polymer with
 2-ethyl-2-[[(1-oxo-2-propenyl)oxy]methyl]-1,3-propanediyl di-2-propenoate,
 α -hydro- ω -[(1-oxo-2-propenyl)oxy]poly(oxy-1,2-ethanediyl)
 ether with 2-ethyl-2-(hydroxymethyl)-1,3-propanediol (3:1), and
 (1-methyl-1,2-ethanediyl)bis[oxy(methyl-2,1-ethanediyl)] di-2-propenoate
 (9CI) (CA INDEX NAME)

CM 1

CRN 42978-66-5

CMF C15 H24 O6

CCI IDS



3 (D1-Me)

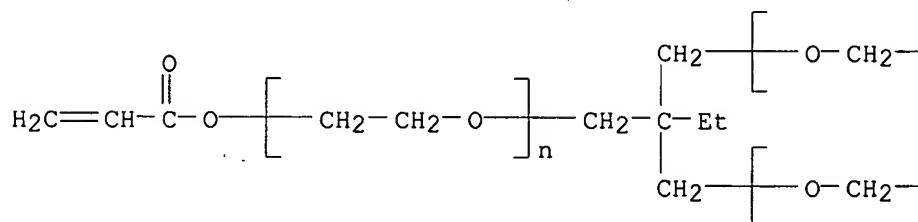
CM 2

CRN 28961-43-5

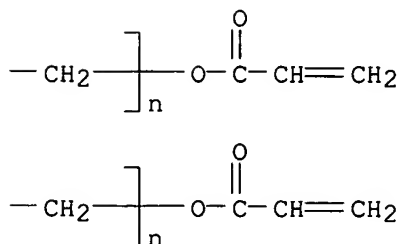
CMF (C2 H4 O)_n (C2 H4 O)_n (C2 H4 O)_n C15 H20 O6

CCI PMS

PAGE 1-A



PAGE 1-B



CM 3

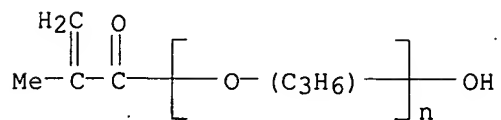
CRN 15625-89-5

CM 1

CRN 39420-45-6

CMF (C3 H6 O)_n C4 H6 O2

CCI IDS, PMS



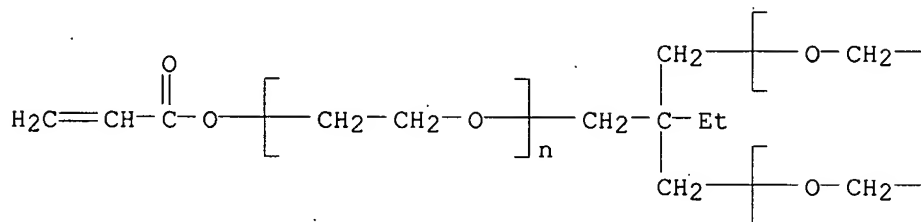
CM 2

CRN 28961-43-5

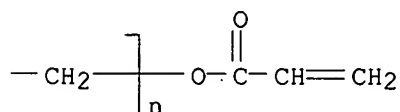
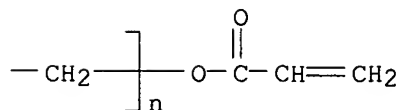
CMF (C2 H4 O)_n (C2 H4 O)_n (C2 H4 O)_n C15 H20 O6

CCI PMS

PAGE 1-A



PAGE 1-B



L90 ANSWER 5 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN

AN 2003:292363 HCAPLUS

DN 139:37136

TI Fabrication of High Aspect Ratio Poly(ethylene glycol)-Containing Microstructures by UV Embossing

AU Chan-Park, Mary B.; Yan, Yehai; Neo, Wee Koon; Zhou, Wenxiu; Zhang, Jun; Yue, Chee Yoon

CS The Biological and Chemical Process Engineering Laboratory, The School of Mechanical and Production Engineering, Nanyang Technological University, Singapore, 639798, Singapore

SO Langmuir (2003), 19(10), 4371-4380

CODEN: LANGD5; ISSN: 0743-7463

PB American Chemical Society

DT Journal

LA English

AB The fabrication of high aspect ratio (5 and above) microstructures based upon UV embossing of mixts. containing poly(ethylene glycol) diacrylate (PEGDA) is described. UV embossing is a quick and convenient replication technique using low pressure and room temperature. The biocompatibility and cell- and protein-resistance of PEGDA make deep three-dimensional (3-D) micropatterned PEGDA films potentially useful for many biol. applications such as protein delivery, tissue engineering, drug delivery, and biosensors. Microarrays of deep microchannels and microcups separated by PEGDA walls with aspect ratios of 7 and 5, resp., were successfully embossed. UV embossing was found to faithfully replicate the lateral periodicity and height of the mold. We also successfully UV embossed a mixture having equal weight proportions of hydrophilic PEGDA and hydrophobic poly(propylene glycol) diacrylate and demonstrated the use of this microarray of microcups for encapsulation of a model protein (bovine serum albumin) within a UV cured PEGDA hydrogel; a protein encapsulated within a hydrogel 3-D microarray was fabricated. Although high aspect ratio UV embossing has many attractive features, it is a difficult process to implement, requiring precise control and optimization of mold, process, and material parameters. Successful high aspect ratio UV embossing was achieved using two molds: a rigid nickel mold and a silicone rubber mold. The latter did not require any surface treatment, but the nickel mold was found to require coating with a cured silicone resin to obtain a suitable nonstick surface. The UV exposure time was controlled to optimize the hardened resin strength while avoiding excessive brittleness. Peel-off of the hardened microstructures was performed at a small angle to avoid breakage of the molded structures. A mold release additive was necessary for successful demolding. Trimethylolpropane triacrylate, a high shrinkage monomer, also facilitated demolding.

IT 540475-04-5P

RL: BUU (Biological use, unclassified); PEP (Physical, engineering or chemical process); PRP (Properties); PYP (Physical process); SPN (Synthetic preparation); BIOL (Biological study); PREP (Preparation); PROC (Process); USES (Uses)

(fabrication of high aspect ratio polyethylene glycol-containing microstructures by UV embossing)

RN 540475-04-5 HCAPLUS

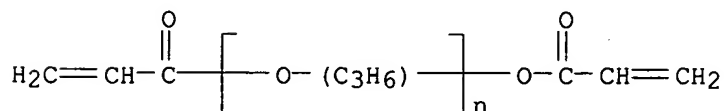
CN 2-Propenoic acid, 2-ethyl-2-[[(1-oxo-2-propenyl)oxy]methyl]-1,3-propanediyl ester, polymer with α -(1-oxo-2-propenyl)- ω -(1-oxo-2-propenyl)oxy]poly(oxy-1,2-ethanediyl) and α -(1-oxo-2-propenyl)- ω -(1-oxo-2-propenyl)oxy]poly[oxy(methyl-1,2-ethanediyl)] (9CI) (CA INDEX NAME)

CM 1

CRN 52496-08-9

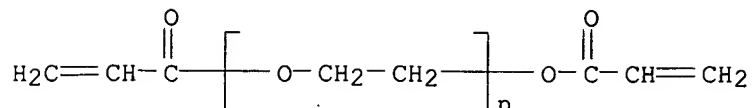
CMF (C3 H6 O)_n C6 H6 O3

CCI IDS, PMS



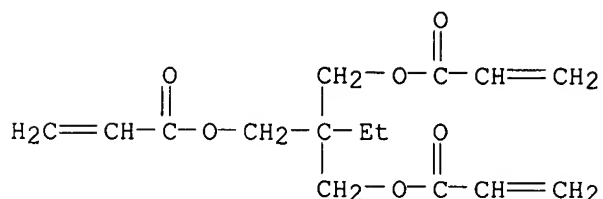
CM 2

CRN 26570-48-9
CMF (C2 H4 O)n C6 H6 O3
CCI PMS



CM 3

CRN 15625-89-5
CMF C15 H20 O6



RETABLE

Referenced Author (RAU)	Year (RPY)	VOL (RVL)	PG (RPG)	Referenced Work (RWK)	Referenced File
Bacher, W	1998	4	117	Microsyst Technol	
Bao, Z	1999	9	1895	J Mater Chem	HCAPLUS
Becker, H	2000	83	130	Sens Actuators, A: P	
Bender, M	2000	53	233	Microelectron Eng	HCAPLUS
Blawas, A	1998	19	595	Biomaterials	HCAPLUS
Brandrup, J	1999			Polymer Handbook	
Bryant, S	2001	22	619	Biomaterials	HCAPLUS
Bryant, S	2000	5	439	J Biomater Sci, Poly	
Calixto, S	1999	8	29	Eur Phys J: Appl Phy	HCAPLUS
Chou, S	1995	67	3114	Appl Phys Lett	HCAPLUS
Chou, S	1996	272	85	Science	HCAPLUS
Colburn, M	2001	19	2162	J Vac Sci Technol, B	HCAPLUS
Desai, N	1991	25	829	J Biomed Mater Res	HCAPLUS
Eldada, L	2000	6	54	IEEE J Sel Top Quant	HCAPLUS
Elisseeff, J	2000	51	164	J Biomed Mater Res	HCAPLUS
Gale, M	1997			Micro-Optics:Element	
Gale, M	1997	34	321	Microelectron Eng	HCAPLUS
Gaspar, S	2001	73	4254	Anal Chem	HCAPLUS
Goessl, A	2001	12	721	J Biomater Sci Polym	HCAPLUS
Haisma, J	1996	14	4124	J Vac Sci Technol, B	HCAPLUS
Halik, M	2002	81	289	Appl Phys Lett	HCAPLUS
Harvey, T	1997	3099	76	Proc SPIE	
Ichimura, K	1987	188	763	Makromol Chem	HCAPLUS
Imai, K	1986	28	1721	Biotechnol Bioeng	HCAPLUS
Jaszewski, R	1999	143	301	Appl Surf Sci	HCAPLUS
Jiang, X	2002	18	2607	Langmuir	HCAPLUS
Koh, W	2002	18	2459	Langmuir	HCAPLUS
Lebib, A	1999	46	319	Microelectron Eng	

Lee, J	1989	23	351	J Biomed Mater Res	HCAPLUS
Lee, K	1995	13	3012	J Vac Sci Technol, B	HCAPLUS
Leewis, C	2001	181	367	Nucl Instrum Methods	HCAPLUS
Liu, V	2002	60	126	J Biomed Mater Res	HCAPLUS
Madou, M	1997			Fundamentals of Micr	
Mellott, M	2001	22	929	Biomaterials	HCAPLUS
Michel, B	2001	45	697	IBM J Res Dev	HCAPLUS
Minnema, L	1988	28	815	Polym Eng Sci	HCAPLUS
Ostuni, E	2000	16	7811	Langmuir	HCAPLUS
Otto, M	2001	57	361	Microelectron Eng	
Pugmire, D	2002	74	871	Anal Chem	HCAPLUS
Revzin, A	2001	17	5440	Langmuir	HCAPLUS
Santini, J	2000	39	2396	Angew Chem, Int Ed	HCAPLUS
Sawhney, A	1993	26	581	Macromolecules	HCAPLUS
Schadt, M	2001	364	151	Mol Cryst Liq Cryst	HCAPLUS
Shvartsman, F	1991	1461	313	Proc SPIE	HCAPLUS
Shvartsman, F	1991	1507	383	Proc SPIE	
Tada, K	1999	38	1143	Jpn J Appl Phys, Par	
Ward, J	2001	56	351	J Biomed Mater Res	HCAPLUS
Wen, M	2002	35	112	Macromolecules	HCAPLUS
Xia, Y	1998	37	550	Angew Chem, Int Ed	HCAPLUS
Xia, Y	1995	117	9576	J Am Chem Soc	HCAPLUS
Zee, F	2001	72	120	Sens Actuators, B: C	

L90 ANSWER 6 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN

AN 2002:756072 HCAPLUS

DN 138:160971

TI Synthesis and characterization of poly(methyl methacrylate-methacrylic acid) for a UV-sensitive aqueous base developable lithographic plate

AU Kiatkamjornwong, Suda; Tessiri, Suteera

CS Department of Imaging and Printing Technology, Faculty of Science, Chulalongkorn University, Bangkok, 10330, Thailand

SO Journal of Applied Polymer Science (2002), 86(8), 1829-1837

CODEN: JAPNAB; ISSN: 0021-8995

PB John Wiley & Sons, Inc.

DT Journal

LA English

AB Syntheses of the copolymers of Me methacrylate and methacrylic acid were carried out by free radical chain polymerization in the presence of benzoyl peroxide (BPO) as an initiator. The effects of the monomer ratio and polymerization time on the averaged mol. wts., polydispersity index, and glass transition temperature were investigated. FTIR and NMR were used for functional

group characterization, GPC for average mol. wts. and the distribution, elemental anal. for CHO content, and DSC for the glass transition temperature. The copolymers were mixed with tripropylene glycol diacrylate (TPGDA) and trimethylol propane ethoxylated triacrylate (TMPEOTA), 2-hydroxy-2-methyl-1-phenyl-propan-1-one (Darocur 1173) and benzophenone (Darocur BP) with anthraquinone for visibility of images. The photosensitive coating was spin-coated onto the anodized aluminum plate on which a thin film was formed. The wet film was then coated with PVA solution as an oxygen barrier layer. The plate assembled with a control wedge and a black color separation film was exposed to UV radiation at different exposure times. The plate was developed in a dilute alkaline developer. The resulting plate was evaluated for its reproduction properties in terms of surface properties (hydrophilic/hydrophobicity) by contact angle measurement of image/nonimage areas, resolution by microline, tone reproduction, and adhesion tests. The article describes the results of the syntheses, characterizations, and uses of the copolymer as a binder of a neg., lithog. printing plate. The present lithog. printing plate is good for a

medium viscosity printing ink to produce medium printing quality on uncoated paper.

IT 181260-01-5

RL: DEV (Device component use); PRP (Properties); USES (Uses)
(imaging characteristics of lithog. printing plates prepared with photoimaging coating containing Me methacrylate-methacrylic acid copolymer binder)

RN 181260-01-5 HCAPLUS

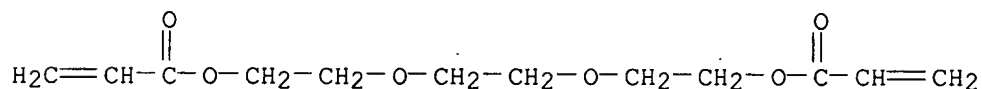
CN 2-Propenoic acid, (1-methyl-1,2-ethanediyl)bis[oxy(methyl-2,1-ethanediyl)] ester, polymer with α -hydro- ω -[(1-oxo-2-propenyl)oxy][poly(oxy-1,2-ethanediyl)] ether with 2-ethyl-2-(hydroxymethyl)-1,3-propanediol (3:1) (9CI) (CA INDEX NAME)

CM 1

CRN 42978-66-5

CMF C15 H24 O6

CCI IDS



3 (D1-Me)

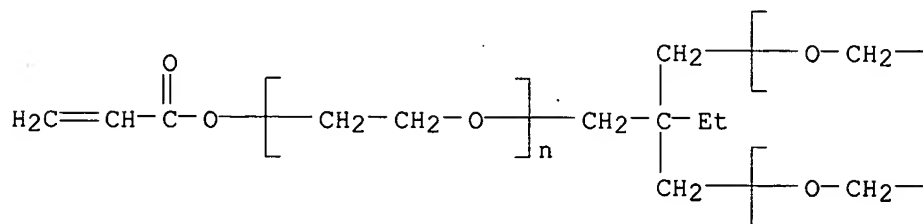
CM 2

CRN 28961-43-5

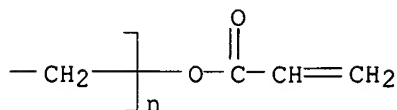
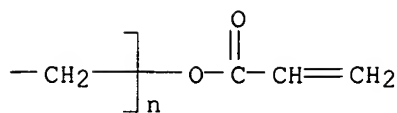
CMF (C2 H4 O)n (C2 H4 O)n (C2 H4 O)n C15 H20 O6

CCI PMS

PAGE 1-A



PAGE 1-B



RETABLE

Referenced Author (RAU)	Year (RPY)	VOL (RVL)	PG (RPG)	Referenced Work (RWK)	Referenced File
Andrews, R	1999		II232	Polymer Handbook	
Chandross, E	1987			US 4666820	HCAPLUS
Dietliker, K	1991	3	70	Photoinitiators for	
Dufour, P	1991	4	34	Formulation	
Fouassier, J	1991	2	245	Photoinitiating Syst	
Greenley, R	1999		VI203	Polymer Handbook	
Kamachi, M	1999		II82	Polymer Handbook	
Odian, G	1991		215	Principles of Polyme	
Odian, G	1991		263	Principles of Polyme	
Ueda, A	1999		II/100	Polymer Handbook	

L90 ANSWER 7 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN

AN 2002:503742 HCAPLUS

DN 137:64615

TI Radiation-curable composition for abrasion-resistant coating

IN Muratake, Hiroaki

PA Dainippon Ink and Chemicals, Inc., Japan

SO Jpn. Kokai Tokkyo Koho, 11 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2002188014	A2	20020705	JP 2000-385134	20001219 <--
PRAI	JP 2000-385134		20001219	<--	

AB The composition contains a radiation-curable compound, inorg. particles, and a fibrous material, which provide abrasion-resistant coating on a paper, plastic, glass, or metal substrate. Thus, poly(ethylene oxide) trimethylolpropane ether triacrylate (ETA 300) 75, tripropylene glycol diacrylate (KS TPGDA) 25, powdered Al₂O₃ (WA 500) 20, and ceramic fiber (RF 200/99) 4 parts were mixed, applied on a paper sheet, and electron beam-irradiated in N to give a cured coating showing good Taber abrasion resistance.

IT **181260-01-5P**, Ethoxylated trimethylolpropane triacrylate-tri(propylene glycol) diacrylate copolymer
 RL: IMF (Industrial manufacture); POF (Polymer in formulation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses) (radiation-curable resin coating containing inorg. particles and fibers with abrasion resistance)

RN 181260-01-5 HCAPLUS

CN 2-Propenoic acid, (1-methyl-1,2-ethanediy1)bis[oxy(methyl-2,1-ethanediy1)] ester, polymer with α -hydro- ω -[(1-oxo-2-propenyl)oxy][poly(oxy-

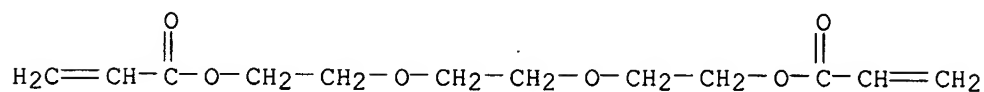
1,2-ethanediyl)] ether with 2-ethyl-2-(hydroxymethyl)-1,3-propanediol
(3:1) (9CI) (CA INDEX NAME)

CM 1

CRN 42978-66-5

CMF C15 H24 O6

CCI IDS



3 (D1-Me)

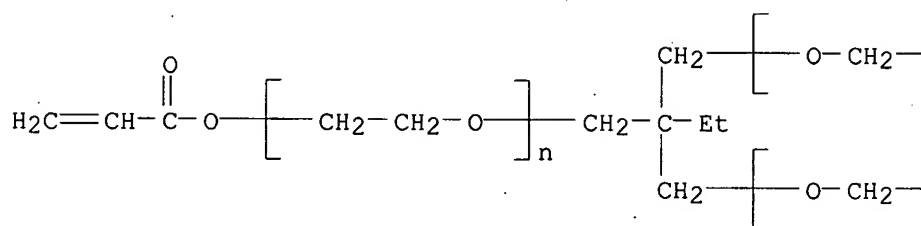
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CRN 28961-43-5

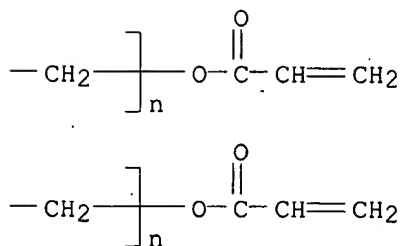
CMF (C2 H4 O)_n (C2 H4 O)_n (C2 H4 O)_n C15 H20 O6

CCI PMS

PAGE 1-A



PAGE 1-B



L90 ANSWER 8 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN

AN 2001:554868 HCAPLUS

DN 135:138793

TI UV-curable protective film compositions for optical recording media and media therefrom

IN Shoji, Toshihiro

PA Dainippon Ink and Chemicals, Inc., Japan

SO Jpn. Kokai Tokkyo Koho, 8 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2001207085	A2	20010731	JP 2000-20056	20000128 <--
	US 2001017819	A1	20010830	US 2001-768178	20010124 <--
	US 6924017	B2	20050802		
	EP 1120447	A1	20010801	EP 2001-101618	20010125 <--
	EP 1120447	B1	20050928		

R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO

PRAI JP 2000-20056 A 20000128 <--

AB Title compns., useful for Ag (alloy)-based reflective film-containing recording media, are characterized with a pH value (A1) of 1% MeOH solution of 4.5-6.8. A composition containing trimethylolpropane triacrylate, ethoxylated

trimethylolpropane triacrylate, tripropylene glycol diacrylate, initiators, and a surfactant showed A1 of 6.4 and was used to form a compact disk showing CI error 2.0 counts/s initially and 10.0 counts/s after 100 h at 80° and 80% relative humidity.

IT 351878-28-9P

RL: IMF (Industrial manufacture); POF (Polymer in formulation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses) (UV-curable acrylic coatings with controlled pH value for Ag (alloy) reflective film-containing optical recording media)

RN 351878-28-9 HCAPLUS

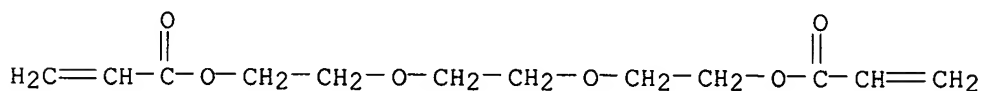
CN 2-Propenoic acid, 2-ethyl-2-[[[(1-oxo-2-propenyl)oxy]methyl]-1,3-propanediyl ester, polymer with α -hydro- ω -[(1-oxo-2-propenyl)oxy]poly(oxy-1,2-ethanediyl) ether with 2-ethyl-2-(hydroxymethyl)-1,3-propanediol (3:1) and (1-methyl-1,2-ethanediyl)bis[oxy(methyl-2,1-ethanediyl)] di-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 42978-66-5

CMF C15 H24 O6

CCI IDS



3 (D1-Me)

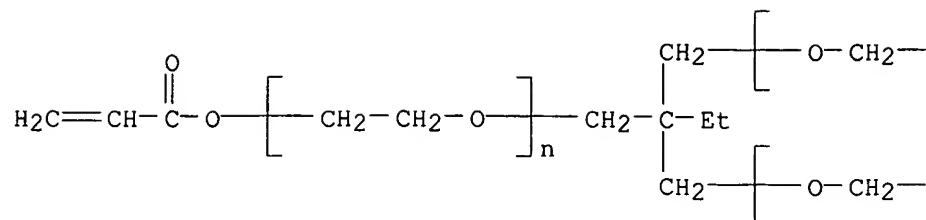
CM 2

CRN 28961-43-5

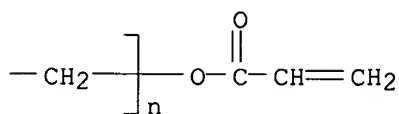
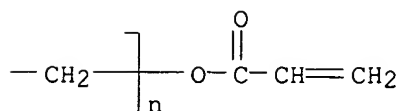
CMF (C2 H4 O)n (C2 H4 O)n (C2 H4 O)n C15 H20 O6

CCI PMS

PAGE 1-A



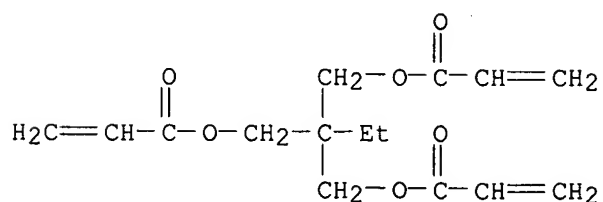
PAGE 1-B



CM 3

CRN 15625-89-5

CMF C15 H20 O6



L90 ANSWER 9 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN
 AN 2001:451291 HCAPLUS
 DN 135:63758
 TI Polymer electrolyte elements, manufacture of the elements and rolls of the elements, the polymer electrolyte element rolls, and manufacture of batteries
 IN Amanokura, Hitoshi; Sonobe, Hiroyuki; Uehara, Hideaki; Saito, Masayasu
 PA Hitachi Chemical Co., Ltd., Japan
 SO Jpn. Kokai Tokkyo Koho, 15 pp.
 CODEN: JKXXAF
 DT Patent
 LA Japanese
 FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2001167638	A2	20010622	JP 1999-348915	19991208 <--
PRAI	JP 1999-348915		19991208	<--	

AB The electrolyte elements have a dried reaction layer of a reactive resin on a support, and are prepared by applying the resin on the support and drying when necessary. Preferably, the reactive resin contains a resin having weight average mol. weight 1000-3,000,000, a ethylenic unsatd. photopolymerizable component, and a photopolymn. initiator. The polymer electrolyte element rolls are prepared by rolling the elements. The batteries are prepared by laminating the polymer electrolyte element, with battery electrodes with the reaction layer in compact with the cathode or anode.

IT **345663-88-9P**

RL: DEV (Device component use); IMF (Industrial manufacture); PREP (Preparation); USES (Uses)

(compns. and manufacture of polymer electrolyte components for secondary lithium batteries)

RN 345663-88-9 HCAPLUS

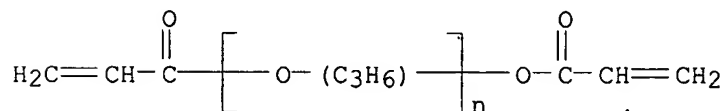
CN Poly[oxy(methyl-1,2-ethanediyl)], α -(1-oxo-2-propenyl)- ω -[(1-oxo-2-propenyl)oxy]-, polymer with α -hydro- ω -hydroxypoly(oxy-1,2-ethanediyl) and α -hydro- ω -[(1-oxo-2-propenyl)oxy]poly(oxy-1,2-ethanediyl) ether with 2-ethyl-2-(hydroxymethyl)-1,3-propanediol (3:1) (9CI) (CA INDEX NAME)

CM 1

CRN 52496-08-9

CMF (C3 H6 O)_n C6 H6 O3

CCI IDS, PMS



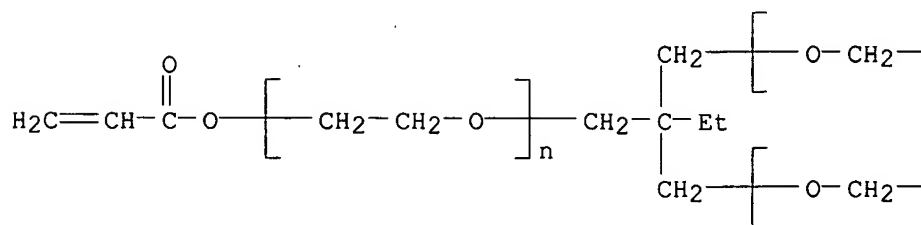
CM 2

CRN 28961-43-5

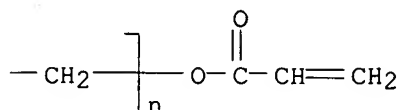
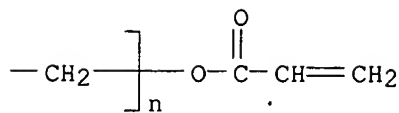
CMF (C2 H4 O)_n (C2 H4 O)_n (C2 H4 O)_n C15 H20 O6

CCI PMS

PAGE 1-A



PAGE 1-B

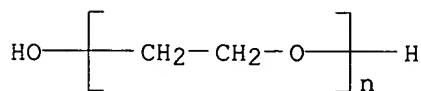


CM 3

CRN 25322-68-3

CMF (C2 H4 O)_n H2 O

CCI PMS



L90 ANSWER 10 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN
 AN 2000:781058 HCAPLUS
 DN 133:336291
 TI Optical polarizing laminates having diffraction elements
 IN Ishimura, Ryo
 PA Nisseki Mitsubishi K. K., Japan
 SO Jpn. Kokai Tokkyo Koho, 17 pp.
 CODEN: JKXXAF
 DT Patent
 LA Japanese
 FAN.CNT 3

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2000310711	A2	20001107	JP 1999-118676	19990426 <--
	WO 2000065383	A1	20001102	WO 2000-JP2587	20000420 <--
	W: CN, KR, US				
	RW: CH, DE, FI, FR, GB, NL				
	US 2002110651	A1	20020815	US 2001-37215	20011019 <--
	US 6875481	B2	20050405		
PRAI	JP 1999-113452	A	19990421	<--	
	JP 1999-118525	A	19990426	<--	
	JP 1999-118676	A	19990426	<--	
	JP 1999-118754	A	19990426	<--	
	JP 1999-175208	A	19990622	<--	
	JP 1999-175253	A	19990622	<--	
	WO 2000-JP2587	A1	20000420	<--	

AB The laminates, useful for optical components, etc., comprise a support substrate, an adhesive layer, a cholesteric liquid crystal layer containing regions having diffraction functions, and a UV-absorbing hard-coating protective layer. Thus, a laminate comprising triacetylcellulose film, a photocurable acrylic adhesive layer, a gold reflective cholesteric liquid crystal layer of 50:20:20:10 terephthalic acid-hydroxybenzoic acid-catechol-(R)-2-methyl-1,4-butanediol copolymer (Tg 85°), which

was treated with a diffraction grating film to impart diffraction and polarizing functions, and a photocurable hard coating layer from acrylic adhesives (mixture of Aronix UV 3630, M 150, and M 315) containing a UV absorber

(Cyasorb UV 24) showed rainbow color derived from optical diffraction, selective reflection, and good wear resistance.

IT 304686-09-7P, Aronix M 240-Aronix M 320 copolymer

RL: IMF (Industrial manufacture); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

(UV-absorbing hard coating layer; polarizing laminates containing cholesteric liquid crystal layers having diffraction functions and UV-absorbing hard coating layers)

RN 304686-09-7 HCAPLUS

CN 2-Propenoic acid, oxybis(2,1-ethanediylxy-2,1-ethanediyl) ester, polymer with α -hydro- ω -[(1-oxo-2-propenyl)oxy]poly[oxy(methyl-1,2-ethanediyl)] ether with 2-ethyl-2-(hydroxymethyl)-1,3-propanediol (3:1) (9CI) (CA INDEX NAME)

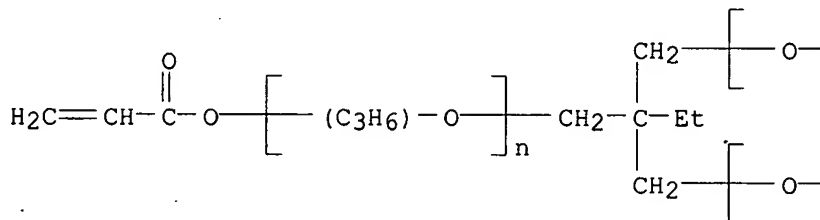
CM 1

CRN 53879-54-2

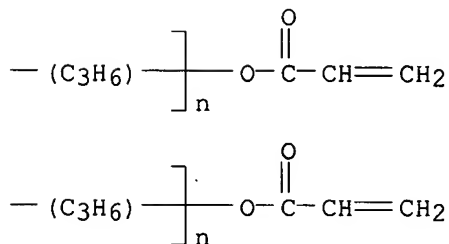
CMF (C3 H6 O)_n (C3 H6 O)_n (C3 H6 O)_n C15 H20 O6

CCI IDS, PMS

PAGE 1-A



PAGE 1-B

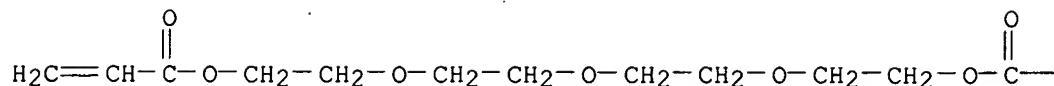


CM 2

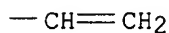
CRN 17831-71-9

CMF C14 H22 O7

PAGE 1-A



PAGE 1-B



L90 ANSWER 11 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN

AN 2000:418045 HCAPLUS

DN 133:65978

TI Photosensitive resin composition, photosensitive element using same, resist pattern formation, and production of printed circuit board

IN Ichikawa, Tatsuya; Ohashi, Takeshi

PA Hitachi Chemical Co., Ltd., Japan

SO Jpn. Kokai Tokkyo Koho, 12 pp.

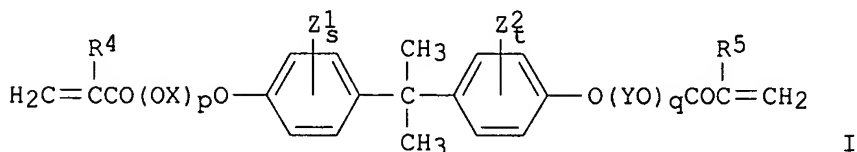
CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2000171971	A2	20000623	JP 1998-345349	19981204 <--
PRAI	JP 1998-345349		19981204	<--	
GI					



AB The title resin composition contains (a) a CO₂H-containing binder polymer, (b) photopolymerizable compounds having ≥1 polymerizable ethylenic unsaturated bond in their molecules including compounds: MeCH₂[CH₂CH₂O(AO)_{m1}(BO)_{n1}COCR₁:CH₂][CH₂CH₂O(AO)_{m2}(BO)_{n2}COCR₂:CH₂][CH₂CH₂O(AO)_{m3}(BO)_{n3}COCR₃:CH₂] [R₁₋₃ = H or Me; A, B = C₂₋₆ alkylene (A ≠ B); m₁ + m₂ + m₃ = 6-45; n₁ + n₂ + n₃ = 3-45] and I [R₄, R₅ = H or Me; X, Y = C₂₋₆ alkylene; Z₁, Z₂ = halo, H, C₁₋₂₀ alkyl, C₃₋₁₀ cycloalkyl, amino- or C₁₋₂₀ alkyl-substituted aryl, amino, SH, C₁₋₁₀ alkylmercapto, C₁₋₁₀ alkyl-containing carboxyalkyl, C₁₋₂₀ alkoxy, heterocycle-containing group; p + q = 8-40; s, t = 1-4] as essential components, and (c) a photopolymerization initiator. The photosensitive element comprises a support laminated with the composition and an optional protective film and is laminated on a substrate for forming a circuit while the protective film is being peeled off, if necessary, imagewise exposed to activating ray to photo-cure the exposed areas, and developed to remove the unexposed areas to form a resist pattern. The substrate on which a

resist pattern has been formed by the above process is subjected to etching or plating to give a printed circuit board. The composition shows high photosensitivity and provides high resolution resist patterns with high plating resistance, adhesivity, mech. strength, and flexibility.

IT 117989-76-1

RL: TEM (Technical or engineered material use); USES (Uses)

(O 565; photoresist composition containing polymer with carboxy group, acrylate

compound, and photopolymn. initiator)

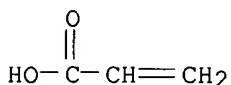
RN 117989-76-1 HCAPLUS

CN Oxirane, methyl-, polymer with oxirane, ether with 2-ethyl-2-(hydroxymethyl)-1,3-propanediol (3:1), tri-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 79-10-7

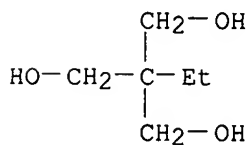
CMF C3 H4 O2



CM 2

CRN 77-99-6

CMF C6 H14 O3



CM 3

CRN 9003-11-6

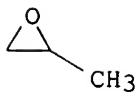
CMF (C3 H6 O . C2 H4 O) x

CCI PMS

CM 4

CRN 75-56-9

CMF C3 H6 O



CM 5

CRN 75-21-8
CMF C2 H4 O



L90 ANSWER 12 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN
AN 2000:188317 HCAPLUS
DN 132:223876
TI Polyacrylate esters and their use as deaerating agents for lacquers and
paints
IN Dietz, Thomas; Esselborn, Eberhard; Psiorz, Christian; Schick, Ute;
Silber, Stefan; Wallhorn, Ellen; Wolfgram, Dirk
PA Th. Goldschmidt A.-G., Germany
SO Ger. Offen., 12 pp.
CODEN: GWXXBX
DT Patent
LA German
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	DE 19841559	A1	20000323	DE 1998-19841559	19980911 <--
	EP 990665	A2	20000405	EP 1999-117003	19990828 <--
	EP 990665	A3	20000524		
	EP 990665	B1	20031001		
	R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO				
	AT 251186	E	20031015	AT 1999-117003	19990828 <--
	CA 2281433	AA	20000311	CA 1999-2281433	19990907 <--
	US 6353068	B1	20020305	US 1999-394441	19990909 <--
PRAI	DE 1998-19841559	A	19980911	<--	

AB The polyacrylates, of average mol. weight 1000-10,000, obtained by transesterification, contain residues formally derived from (a) C1-4-alkyl acrylates, (b) C12-22-alk(en)yl acrylates, and (c) (meth)acryloyloxyhydrocarbyl acrylates in molar ratio (10-50):(3-20):(1-10), where $a/(b + c) = 0.25-4$ and $c/b \leq 0.7$. Thus, 193.3 g poly(Me acrylate) (Mw 3101), obtained by polymerization in toluene with AIBN as initiator and n-dodecyl mercaptan as chain-transfer agent, was heated to 100°/1 torr to remove solvent, then heated at 120°/15 torr with 187.9 g oleyl alc. and 3.92 g Bu₂SnO with MeOH distillation, and finally heated at 50°/60 torr with 46.4 g 2-hydroxyethyl acrylate in the presence of methylhydroquinone as polymerization inhibitor to give a polyacrylate

with a:b:c = 7:7:2. A clear lacquer based on Laromer PO 84F containing 0.5% of the polyacrylate air-sprayed on a wooden board at 100 µm thickness and cured by UV irradiation showed a reduced content of air bubbles by visual observation and by gloss measurement.

IT 261629-46-3, Laromer 8863-OTA 480-TPGDA copolymer
RL: POF (Polymer in formulation); TEM (Technical or engineered material use); USES (Uses)
(lacquer binder; polyacrylate esters as deaerating agents for lacquers and paints)

RN 261629-46-3 HCAPLUS
CN 2-Propenoic acid, (1-methyl-1,2-ethanediyl)bis[oxy(methyl-2,1-ethanediyl)] ester, polymer with α-hydro-ω-[(1-oxo-2-propenyl)oxy]poly(oxy-1,2-ethanediyl) ether with 2-ethyl-2-(hydroxymethyl)-1,3-propanediol (3:1)

and $\alpha, \alpha', \alpha''$ -1,2,3-propanetriyltris[ω -(1-oxo-2-propenyl)oxy]poly[oxy(methyl-1,2-ethanediyl)] (9CI) (CA INDEX NAME)

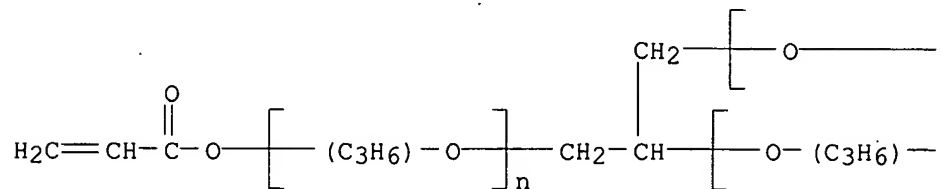
CM 1

CRN 52408-84-1

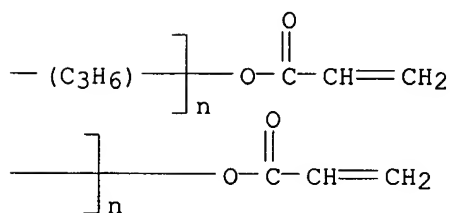
CMF (C3 H6 O)_n (C3 H6 O)_n (C3 H6 O)_n C12 H14 O6

CCI IDS, PMS

PAGE 1-A



PAGE 1-B

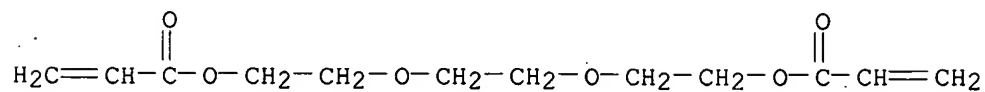


CM 2

CRN 42978-66-5

CMF C15 H24 O6

CCI IDS



3 (D1-Me)

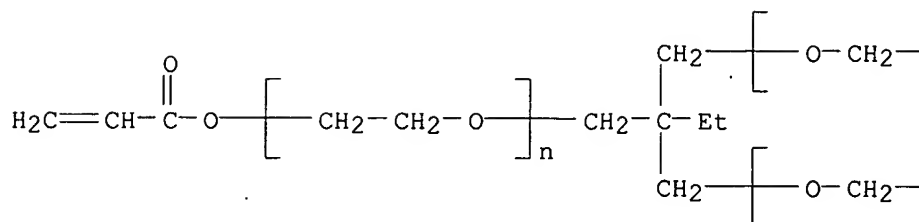
CM 3

CRN 28961-43-5

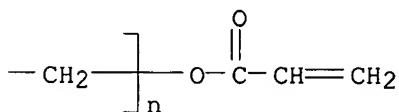
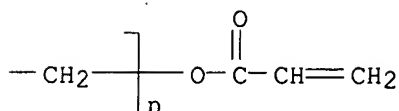
CMF (C2 H4 O)_n (C2 H4 O)_n (C2 H4 O)_n C15 H20 O6

CCI PMS

PAGE 1-A



PAGE 1-B



RETABLE

Referenced Author (RAU)	Year (RPY)	VOL (RVL)	PG (RPG)	Referenced Work (RWK)	Referenced File
=====	=====	=====	=====	=====	=====
Anon				DE 3718588 C1	HCAPLUS
Anon				DE 4236337 C1	HCAPLUS

L90 ANSWER 13 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN

AN 1999:504973 HCAPLUS

DN 131:117642

TI Agents for treating wood

IN Gatenholm, Paul

PA Advanced Polymer Technology AB, Swed.

SO Swed., 12 pp.

CODEN: SSXXAY

DT Patent

LA Swedish

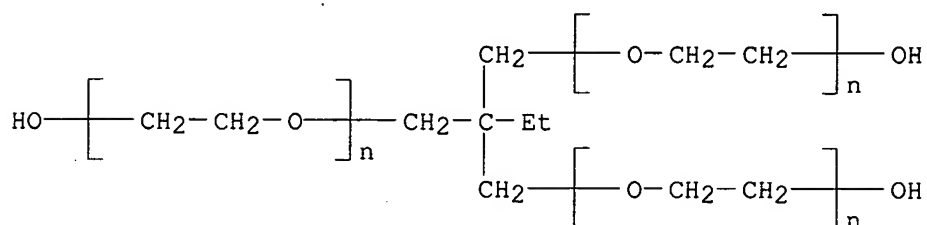
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
	-----	----	-----	-----	-----
PI	SE 508575	C2	19981019	SE 1990-2302	19900629 <--
	SE 9002302	A	19911230		
PRAI	SE 1990-2302		19900629 <--		

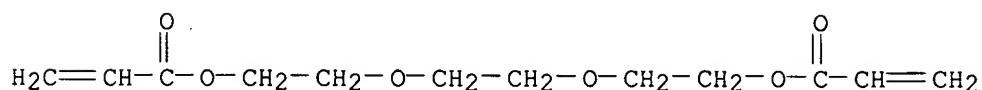
AB The agents, which penetrate the wood and polymerize in the wood to bring about dimensional stabilization of the wood, contain a multifunctional allyl ether and an acrylate- or methacrylate-terminated polyether and/or an acrylate- or methacrylate-terminated urethane prepolymer. These agents are environmentally safe, give good penetration, do not require heat or radiation for drying (polymerizing), and may be used in diluted and undiluted form,

and wood treated with the agents has good weather resistance. An agent containing Santolink XI 100 [oxirane, [(2-propenyloxy)methyl]-, homopolymer, ether with 1,2-ethanediol (2:1)] 20.0, Sartomer 344 (polyethyleneglycol 400 diacrylate) 80.0, and containing Nuocure CK (Co-K complex; drier) 0.3, and

benzoylperoxide 1.0 g, had shelf life 1-8 h and gave penetration 3 mm.
 IT 232611-84-6, Novamer TPGDA-TP 30 copolymer
 RL: FMU (Formation, unclassified); TEM (Technical or engineered material use); FORM (Formation, nonpreparative); USES (Uses)
 (for penetration and wood preservation)
 RN 232611-84-6 HCAPLUS
 CN 2-Propenoic acid, (1-methyl-1,2-ethanediyl)bis[oxy(methyl-2,1-ethanediyl)]
 ester, polymer with α -hydro- ω -hydroxypoly(oxy-1,2-ethanediyl)
 ether with 2-ethyl-2-(hydroxymethyl)-1,3-propanediol (3:1) (9CI) (CA
 INDEX NAME)
 CM 1
 CRN 50586-59-9
 CMF (C2 H4 O)_n (C2 H4 O)_n (C2 H4 O)_n C6 H14 O3
 CCI PMS



CM 2
 CRN 42978-66-5
 CMF C15 H24 O6
 CCI IDS



3 (D1-Me)

L90 ANSWER 14 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN
 AN 1999:322528 HCAPLUS
 DN 131:37785
 TI Photosensitive resin composition and photosensitive element using same
 IN Ichikawa, Tatsuya; Endo, Masaki
 PA Hitachi Chemical Co., Ltd., Japan
 SO Jpn. Kokai Tokkyo Koho, 7 pp.
 CODEN: JKXXAF
 DT Patent
 LA Japanese
 FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 11133595	A2	19990521	JP 1997-294510	19971027 <--

PRAI JP 1997-294510

19971027 <--

AB The title resin composition comprises (a) a CO₂H-containing binder polymer,
(b) a

photopolymn. initiator, and (c) photopolymg. unsatd. compds. having
≥1 polymerizable ethylenic unsatd. bond in their mol. including
5-70 weight% of compound EtC[CH₂O(AO)m₁(BO)n₁COCR₁:CH₂][CH₂O(AO)m₂(BO)n₂COCR₂:C
H₂][CH₂O(AO)m₃(BO)n₃COCR₃:CH₂] (R₁- 3 = H or Me; A, B = CHMeCH₂, CH₂CHMe,
CH₂CH₂, A ≠ B; m₁ + m₂ + m₃ = 6-45; n₁ + n₂ + n₃ = 3-45). The
photosensitive element comprises a support coated with the composition The
composition useful as a resist suited for use in production of printed circuit
boards shows improved plating resistance and peeling properties.

IT 117989-76-1

RL: TEM (Technical or engineered material use); USES (Uses)
(photoresist containing binder polymer with carboxyl group, photopolymn.
initiator, and ethylenic unsaturate photopolymerizable compound)

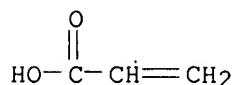
RN 117989-76-1 HCAPLUS

CN Oxirane, methyl-, polymer with oxirane, ether with 2-ethyl-2-
(hydroxymethyl)-1,3-propanediol (3:1), tri-2-propenoate (9CI) (CA INDEX
NAME)

CM 1

CRN 79-10-7

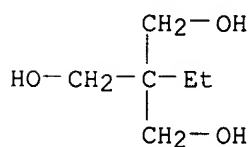
CMF C3 H4 O2



CM 2

CRN 77-99-6

CMF C6 H14 O3



CM 3

CRN 9003-11-6

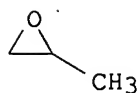
CMF (C3 H6 O . C2 H4 O)x

CCI PMS

CM 4

CRN 75-56-9

CMF C3 H6 O



CM 5

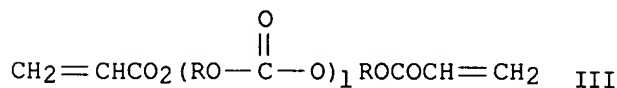
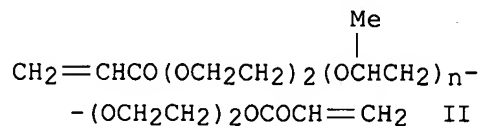
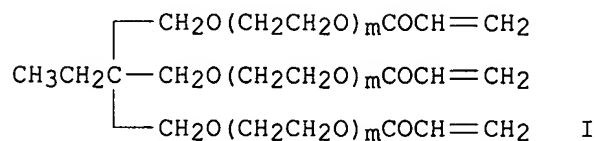
CRN 75-21-8

CMF C2 H4 O



L90 ANSWER 15 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN
 AN 1997:483305 HCAPLUS
 DN 127:111220
 TI Secondary nonaqueous batteries using polymer containing gelled electrolytes
 IN Matsui, Toru; Takeyama, Kenichi
 PA Matsushita Electric Industrial Co., Ltd., Japan
 SO Jpn. Kokai Tokkyo Koho, 6 pp.
 CODEN: JKXXAF
 DT Patent
 LA Japanese
 FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 09147912	A2	19970606	JP 1995-309391	19951128 <--
	JP 3312836	B2	20020812		
PRAI	JP 1995-309391		19951128	<--	
GI					



AB The batteries use gelled alkali metal ion conductive electrolyte containing a

matrix of a copolymer of I (m = an integer) and II (n = an integer) or I and III ($R = (CH_2)_s$ or $[(CH_2)_kO(CH_2)_l]_t$; s, k, l, t are integers). These electrolytes have good interfacial property at the anode side and render the batteries long cycle life.

IT 192189-34-7P

RL: DEV (Device component use); IMF (Industrial manufacture); PEP (Physical, engineering or chemical process); PREP (Preparation); PROC (Process); USES (Uses)

(acrylate copolymer matrixes for gelled electrolytes in lithium batteries)

RN 192189-34-7 HCAPLUS

CN Oxirane, methyl-, polymer with oxirane, di-2-propenoate, block, polymer with α -hydro- ω -[(1-oxo-2-propenyl)oxy]poly(oxy-1,2-ethanediyl) ether with 2-ethyl-2-(hydroxymethyl)-1,3-propanediol (3:1) (9CI) (CA INDEX NAME)

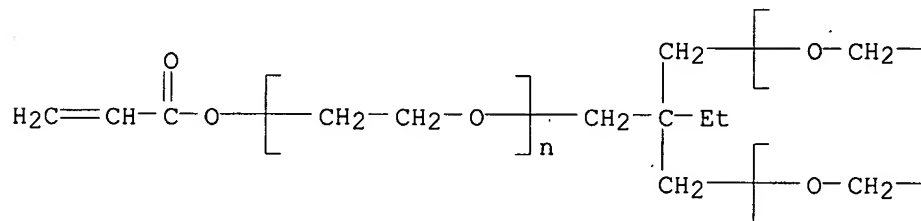
CM 1

CRN 28961-43-5

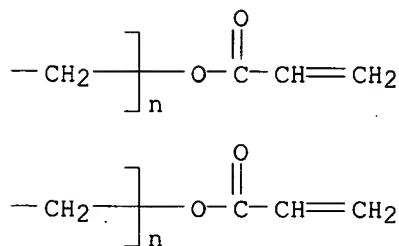
CMF $(C_2 H_4 O)_n (C_2 H_4 O)_n (C_2 H_4 O)_n C_{15} H_{20} O_6$

CCI PMS

PAGE 1-A



PAGE 1-B



CM 2

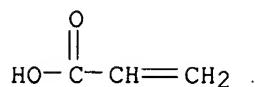
CRN 146702-30-9

CMF $(C_3 H_6 O \cdot C_2 H_4 O)_x \cdot 2 C_3 H_4 O_2$

CM 3

CRN 79-10-7

CMF $C_3 H_4 O_2$



CM 4

CRN 106392-12-5

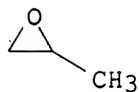
CMF (C3 H6 O . C2 H4 O)x

CCI PMS

CM 5

CRN 75-56-9

CMF C3 H6 O



CM 6

CRN 75-21-8

CMF C2 H4 O



L90 ANSWER 16 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN

AN 1997:479241 HCAPLUS

DN 127:97521

TI Flat non-aqueous electrolyte secondary battery with polymer coated anode

IN Matsui, Tooru; Takeyama, Kenichi

PA Matsushita Electric Industrial Co., Ltd., Japan

SO Eur. Pat. Appl., 13 pp.

CODEN: EPXXDW

DT Patent

LA English

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	EP 777287	A2	19970604	EP 1996-117858	19961107 <--
	EP 777287	A3	19970716		
	EP 777287	B1	20000202		
	R: BE, DE, FR, GB, IT				
	JP 09147920	A2	19970606	JP 1995-309381	19951128 <--
	JP 3394125	B2	20030407		
	US 5773166	A	19980630	US 1996-756778	19961126 <--
PRAI	JP 1995-309381	A	19951128	<--	

AB The flat non-aqueous electrolyte secondary battery has an anode containing an alkali metal (e.g., lithium) active material, where the anode is coated with a polymer film containing dissociated alkali metal ions, supporting a gel electrolyte. The polymer film is made of a polymeric monomer which has

mol. weight/terminal polymer functional group number of ≤ 500 , and a alkoxyated polyol acrylate structure where the alkoxyated chains are formed by random or block polymerization of ethylene oxide and/or propylene oxide.

IT 117989-76-1

RL: DEV (Device component use); TEM (Technical or engineered material use); USES (Uses)

(flat non-aqueous electrolyte secondary alkali metal battery with polymer coated anode)

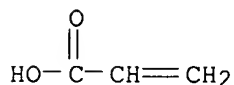
RN 117989-76-1 HCAPLUS

CN Oxirane, methyl-, polymer with oxirane, ether with 2-ethyl-2-(hydroxymethyl)-1,3-propanediol (3:1), tri-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 79-10-7

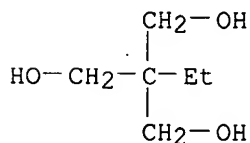
CMF C3 H4 O2



CM 2

CRN 77-99-6

CMF C6 H14 O3



CM 3

CRN 9003-11-6

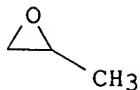
CMF (C3 H6 O . C2 H4 O)x

CCI PMS

CM 4

CRN 75-56-9

CMF C3 H6 O



CM 5

CRN 75-21-8
CMF C2 H4 O



L90 ANSWER 17 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN

AN 1997:369593 HCAPLUS

DN 126:344211

TI Continuous process for the preparation of highly stable, finely divided, low viscosity polymer polyols of small average particle size

IN Kratz, Mark R.; Dietrich, Manfred; Heinemann, Torsten; Jacobs, Gundolf; Sanders, Josef; Woynar, Helmut

PA Bayer A.-G., Germany

SO Eur. Pat. Appl., 14 pp.

CODEN: EPXXDW

DT Patent

LA English

FAN.CNT 1

	PATENT NO:	KIND	DATE	APPLICATION NO.	DATE
PI	EP 768324	A1	19970416	EP 1995-115940	19951010 <--
	EP 768324	B1	20000816		
	R: BE, DE, ES, FR, GB, IT, NL				
	ES 2148397	T3	20001016	ES 1995-115940	19951010 <--
	US 5814699	A	19980929	US 1996-723659	19961003 <--
	CA 2187125	AA	19970411	CA 1996-2187125	19961004 <--
	JP 09124750	A2	19970513	JP 1996-285938	19961009 <--
	BR 9605032	A	19980630	BR 1996-5032	19961009 <--
	CN 1160061	A	19970924	CN 1996-112759	19961010 <--
	CN 1069654	B	20010815		
PRAI	EP 1995-115940	A	19951010	<--	

OS MARPAT 126:344211

AB Highly stable, finely divided, low viscosity polymer polyols of small average particle size, useful for preparation of polyurethane foams, are manufacture by 1st

reacting (1) a mixture of styrene and acrylonitrile (I) in a mixture of (2) a polyoxyalkylene polyether polyol and (3) a macromer in the presence of (4) a free radical initiator, (5) a solvent having moderate chain transfer activity and optionally (6) a reaction moderator at a temperature of $\geq 100^\circ$ to give a seed with macromer content $\geq 12\%$ with respect to the polyol mixture and the solids content 15-30%, and then using the seed in further stirred-tank reactors for a similar polymerization of

styrene

with I but optionally in the presence of a macromer. A typical macromer was manufactured by reaction of ethylene oxide-propylene oxide copolymer trimethylolpropane ether with maleic anhydride and subsequently with ethylene oxide.

IT 118800-30-9P

RL: IMF (Industrial manufacture); RCT (Reactant); PREP (Preparation); RACT (Reactant or reagent)

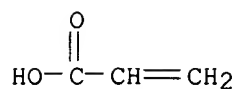
(macromer; continuous manufacture of highly stable, finely divided, low viscosity polymer polyols of small average particle size from macromers for polyurethane foams)

RN 118800-30-9 HCAPLUS

CN Oxirane, methyl-, polymer with oxirane, ether with 2-ethyl-2-(hydroxymethyl)-1,3-propanediol (3:1), 2-propenoate (9CI) (CA INDEX NAME)

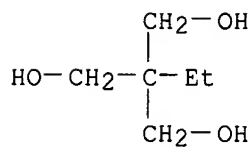
CM 1

CRN 79-10-7
CMF C3 H4 O2



CM 2

CRN 77-99-6
CMF C6 H14 O3

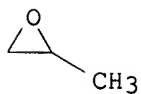


CM 3

CRN 9003-11-6
CMF (C3 H6 O . C2 H4 O)x
CCI PMS

CM 4

CRN 75-56-9
CMF C3 H6 O



CM 5

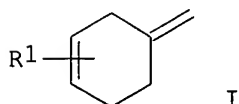
CRN 75-21-8
CMF C2 H4 O



L90 ANSWER 18 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN
AN 1996:580576 HCAPLUS
DN 125:302320
TI Low viscosity polymer polyols, a process for their production, and

IN manufacture of polyurethane from materials
 Sanders, Josef; Kratz, Mark; Dietrich, Manfred; Heinemann, Torsten;
 Woynar, Helmut; Jacobs, Gundolf; Scholz, Uwe
 PA Bayer Aktiengesellschaft, Germany.
 SO U.S., 10 pp.
 CODEN: USXXAM
 DT Patent
 LA English
 FAN.CNT 2

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	US 5554662	A	19960910	US 1995-470695	19950606 <--
PRAI	DE 1995-19508578	A	19950310	<--	
OS	MARPAT 125:302320				
GI					



AB Stable, agglomerate-free, low viscosity graft copolymer dispersions are produced by radical polymerization of ethylenically unsatd. monomers in the presence of a base polyol, a macromer, an enol ether chain-transfer agent A=CHOR (A is I; R is a C1-18 aliphatic hydrocarbon radical, a C5-10 cycloaliph. hydrocarbon radical, or a (substituted) benzyl radical; R' is H or a C1-8 aliphatic hydrocarbon radical), and optionally, an organic solvent. Acrylonitrile and styrene were polymerized with ethylene trimethylolpropane-initiated oxide-propylene oxide copolymer acrylate macromer in the presence of cyclohex-3-enylidene-cyclohexyl ether to give a graft copolymer which was used in manufacture of a polyurethane foam.

IT 118800-30-9P

RL: IMF (Industrial manufacture); RCT (Reactant); PREP (Preparation); RACT (Reactant or reagent)

(low viscosity polymer polyols, a process for their production, and manufacture

of polyurethane from materials)

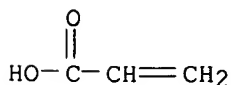
RN 118800-30-9 HCAPLUS

CN Oxirane, methyl-, polymer with oxirane, ether with 2-ethyl-2-(hydroxymethyl)-1,3-propanediol (3:1), 2-propenoate (9CI) (CA INDEX NAME)

CM 1

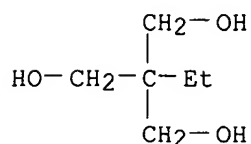
CRN 79-10-7

CMF C3 H4 O2



CM 2

CRN 77-99-6
CMF C6 H14 O3

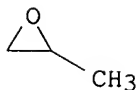


CM 3

CRN 9003-11-6
CMF (C3 H6 O . C2 H4 O)x
CCI PMS

CM 4

CRN 75-56-9
CMF C3 H6 O



CM 5

CRN 75-21-8
CMF C2 H4 O



L90 ANSWER 19 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN
AN 1996:577028 HCAPLUS
DN 125:198103
TI Scratch-resistant antistatic plastic films or sheets and their manufacture
IN Yamakido, Masayoshi; Ihira, Makoto; Araki, Mineo
PA Takiron Co, Japan
SO Jpn. Kokai Tokkyo Koho, 8 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 08169967	A2	19960702	JP 1994-334814	19941219 <--
	JP 3503035	B2	20040302		
PRAI	JP 1994-334814		19941219	<--	
AB	Title films or sheets are prepared by dispersing elec. conductive polyaniline in multifunctional acrylate monomer solns., coating one or two sides of plastic films or sheets with the dispersions, and curing the				

acrylates by electron beam irradiation and optionally laminating the films as the outer layer with plastic sheets. Thus, 100 parts Aronix M 350 (ethoxylated trimethylolpropane triacrylate) was mixed with 10 parts Versicon (polyaniline), applied onto poly(Me methacrylate) film on one side, and cured by electron beam irradiation at 2 Mrad doses to form an antistatic film. PVC was sandwiched between two of the film and hot pressed to give an antistatic sheet exhibiting surface resistivity $2.4 \times 10^6 \Omega$ initially and $3.7 \times 10^6 \Omega$ after abrading the surface for 100 cycles at load 250 g using a Taber abrader, light transmittance 37.4% initially and 37.4% after the abrasion test, and haze 20.5% initially and 28.3% after the abrasion test.

IT 181260-01-5P

RL: IMF (Industrial manufacture); POF (Polymer in formulation); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

(coating, containing polyaniline; for manufacture of scratch-resistant antistatic plastic films or sheets)

RN 181260-01-5 HCAPLUS

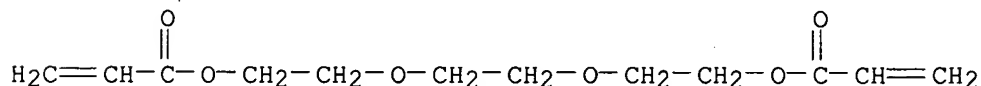
CN 2-Propenoic acid, (1-methyl-1,2-ethanediyl)bis[oxy(methyl-2,1-ethanediyl)] ester, polymer with α -hydro- ω -[(1-oxo-2-propenyl)oxy][poly(oxy-1,2-ethanediyl)] ether with 2-ethyl-2-(hydroxymethyl)-1,3-propanediol (3:1) (9CI) (CA INDEX NAME)

CM 1

CRN 42978-66-5

CMF C15 H24 O6

CCI IDS



3 (D1-Me)

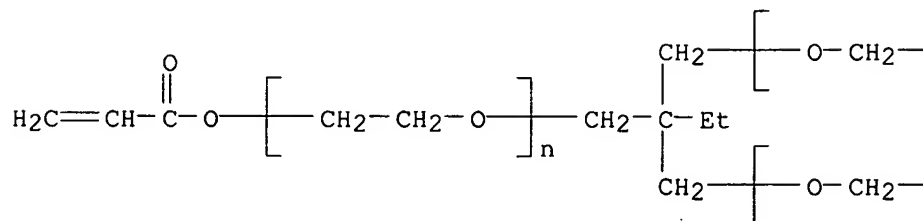
CM 2

CRN 28961-43-5

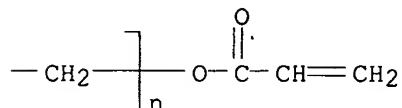
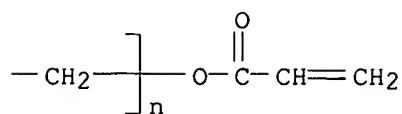
CMF (C2 H4 O)_n (C2 H4 O)_n (C2 H4 O)_n C15 H20 O6

CCI PMS

PAGE 1-A



PAGE 1-B



L90 ANSWER 20 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN
 AN 1995:808429 HCAPLUS
 DN 123:270912
 TI Liquid crystal/prepolymer compositions and liquid-crystal display devices using them
 IN Takiguchi, Yasuyuki; Kanemoto, Akihiko; Matsuki, Yumi
 PA Ricoh Kk, Japan
 SO Jpn. Kokai Tokkyo Koho, 14 pp.
 CODEN: JKXXAF
 DT Patent
 LA Japanese
 FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 07175051	A2	19950714	JP 1994-82301	19940329 <--
	US 5496497	A	19960305	US 1994-220699	19940331 <--
PRAI	JP 1993-97182	A	19930331	<--	
	JP 1993-298888	A	19931104	<--	

AB The compns. contain a prepolymer composition, which mainly comprises bifunctional acrylates having 2 double bonds with HLB value 3.5-11 and monofunctional acrylates having 1 double bond with HLB value 2.5-7.0, a polymerization initiator, and a liquid crystal and in which phase separation between the liquid crystal and the polymer is induced by polymerization. The liquid-crystal display devices comprise a pair of substrates, between which the liquid crystal/polymer phase-separated structure formed by polymerization of the above compns. is supported. The display devices are capable of being driven at low voltage and show sharp threshold characteristics, low hysteresis, high-speed response, and high charge retention.

IT 169122-13-8P
 RL: PNU (Preparation, unclassified); POF (Polymer in formulation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses) (liquid-crystal/prepolymer compns. containing HLB-controlled mono- and diacrylates for polymer-dispersed liquid-crystal display devices)

RN 169122-13-8 HCAPLUS
 CN 2-Propenoic acid, 2-ethyl-2-[[[(1-oxo-2-propenyl)oxy]methyl]-1,3-propanediyl ester, polymer with α -(1-oxo-2-propenyl)- ω -(dodecyloxy)poly(oxy-1,2-ethanediyl) and α -(1-oxo-2-propenyl)- ω -[(1-oxo-2-propenyl)oxy]poly[oxy(methyl-1,2-ethanediyl)] (9CI) (CA INDEX NAME)

CM 1

CRN 52496-08-9
 CMF (C3 H6 O)_n C6 H6 O3
 CCI IDS, PMS

photosensitive composition layer are claimed. The composition shows good flexibility, releasing property, and plating resistance, and prevents generation of scum.

IT 117989-76-1 161278-82-6

RL: TEM (Technical or engineered material use); USES (Uses)

(photoresist containing propoxy ethoxy acrylate and organic halo compound)

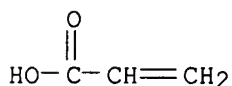
RN 117989-76-1 HCAPLUS

CN Oxirane, methyl-, polymer with oxirane, ether with 2-ethyl-2-(hydroxymethyl)-1,3-propanediol (3:1), tri-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 79-10-7

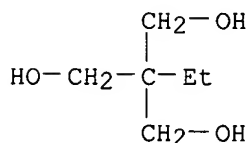
CMF C3 H4 O2



CM 2

CRN 77-99-6

CMF C6 H14 O3



CM 3

CRN 9003-11-6

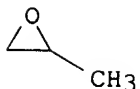
CMF (C3 H6 O . C2 H4 O) x

CCI PMS

CM 4

CRN 75-56-9

CMF C3 H6 O



CM 5

CRN 75-21-8

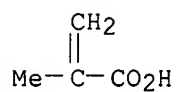
CMF C2 H4 O



RN 161278-82-6 HCAPLUS
 CN Oxirane, methyl-, polymer with oxirane, ether with 2-ethyl-2-(hydroxymethyl)-1,3-propanediol (3:1), tris(2-methyl-2-propenoate) (9CI)
 (CA INDEX NAME)

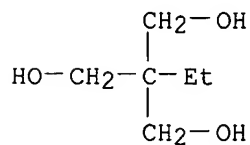
CM 1

CRN 79-41-4
 CMF C4 H6 O2



CM 2

CRN 77-99-6
 CMF C6 H14 O3

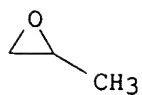


CM 3

CRN 9003-11-6
 CMF (C3 H6 O . C2 H4 O) x
 CCI PMS

CM 4

CRN 75-56-9
 CMF C3 H6 O



CM 5

CRN 75-21-8
 CMF C2 H4 O



L90 ANSWER 22 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN

AN 1995:227405 HCAPLUS

DN 122:92840

TI Crosslinking curable resin composition

IN Kushi, Kenji; Inukai, Kenichi; Iseki, Takayuki; Koyanagi, Seiya

PA Mitsubishi Rayon Co., Ltd., Japan

SO U.S., 13 pp.

CODEN: USXXAM

DT Patent

LA English

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	US 5356754	A	19941018	US 1992-950500	19920925 <--
PRAI	US 1992-950500		19920925 <--		

AB A photopolymerizable or radiation polymerizable alkaline developing crosslinking curable resin composition comprises: (a) 5-30 parts by weight of at

least one compound possessing in one mol. on the average 1.5 or more (meth)acryloyloxy groups, which is obtained by reacting (meth)acrylic acid with a reaction product formed by adding, to a polyat. alc. possessing 3 or more OH groups in one mol., an alkylene oxide containing propylene oxide in an amount of 67% molar or greater in an amount of 5-12 mol per mol of OH group in the aforementioned polyat. alc., (b) 5-30 parts by weight of at least one crosslinkable monomer other than that stated above in (a), possessing in one mol. 2 or more ethylenically unsatd. groups, (c) 45-75 parts by weight of a thermoplastic polymer for use as a binder, the thermoplastic polymer in turn being formed of 15-35 weight% of at least one α , β -unsatd. carboxyl group containing a monomer having 3-15 carbon atoms, and 65-85 weight

% of another copolymerizable monomer, and (d) 0-10 parts by weight of a photopolymn. initiator. The composition possesses superior antiplating properties and a short stripping period, in which the stripped plate is not easily dissolved in the stripping fluid.

IT 118800-30-9P

RL: POF (Polymer in formulation); SPN (Synthetic preparation); PREP (Preparation); USES (Uses)

(crosslinking curable resin composition)

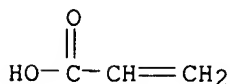
RN 118800-30-9 HCAPLUS

CN Oxirane, methyl-, polymer with oxirane, ether with 2-ethyl-2-(hydroxymethyl)-1,3-propanediol (3:1), 2-propenoate (9CI) (CA INDEX NAME)

CM 1

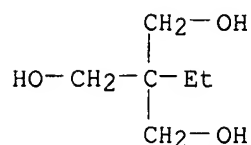
CRN 79-10-7

CMF C3 H4 O2



CM 2

CRN 77-99-6
CMF C6 H14 O3

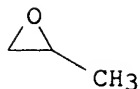


CM 3

CRN 9003-11-6
CMF (C3 H6 O . C2 H4 O)x
CCI PMS

CM 4

CRN 75-56-9
CMF C3 H6 O



CM 5

CRN 75-21-8
CMF C2 H4 O



L90 ANSWER 23 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN
AN 1994:334936 HCAPLUS
DN 120:334936
TI Novel (meth)acrylate for photoresists
IN Myazaki, Seiji; Myoshi, Takanori; Sonobe, Hiroshi; Koyanagi, Seiya
PA Mitsubishi Rayon Co, Japan
SO Jpn. Kokai Tokkyo Koho, 5 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 05125015	A2	19930521	JP 1991-289960	19911106 <--
PRAI	JP 1991-289960		19911106	<--	
AB	The claimed acrylate is obtained by forming an adduct of alkylene oxides to a polyhydric alc., then esterifying; the polyhydric alc. containing ≥3 OH in 1 mol., the alkylene oxide being propylene oxide or its				

mixture with ethylene oxide (propylene oxide ≥ 67 mol%), the addition amount of alkylene oxides to polyhydric alc. being average 5-12 mol/mol(OH), and

there existing average ≥ 1.5 (meth)acrylate ester group in 1 mol.. The (meth)acrylate shows superior plating-resistance, easy peeling off property and low irritation to skin.

IT 118800-30-9P

RL: SPN (Synthetic preparation); PREP (Preparation)
(preparation and use of, as photoresist composition)

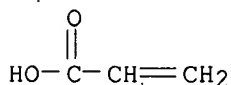
RN 118800-30-9 HCAPLUS

CN Oxirane, methyl-, polymer with oxirane, ether with 2-ethyl-2-(hydroxymethyl)-1,3-propanediol (3:1), 2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 79-10-7

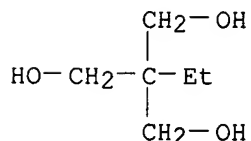
CMF C3 H4 O2



CM 2

CRN 77-99-6

CMF C6 H14 O3



CM 3

CRN 9003-11-6

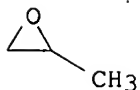
CMF (C3 H6 O . C2 H4 O)x

CCI PMS

CM 4

CRN 75-56-9

CMF C3 H6 O



CM 5

CRN 75-21-8

CMF C2 H4 O



L90 ANSWER 24 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN
 AN 1993:683964 HCAPLUS
 DN 119:283964
 TI Solid electrolytes and their preparation
 IN Kono, Michiyuki; Motogami, Kenji; Mori, Shigeo
 PA Daiichi Kogyo Seiyaku Co., Ltd., Japan
 SO Eur. Pat. Appl., 11 pp.

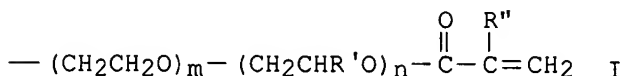
CODEN: EPXXDW

DT Patent
 LA English

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	EP 537930	A1	19930421	EP 1992-309063	19921005 <--
	EP 537930	B1	19950524		
	R: DE, FR, GB, NL				
	JP 05109311	A2	19930430	JP 1991-296173	19911015 <--
	JP 2987474	B2	19991206		
	US 5356553	A	19941018	US 1992-957258	19921006 <--
	CA 2080047	AA	19930416	CA 1992-2080047	19921007 <--
	CA 2080047	C	19990302		
PRAI	JP 1991-296173	A	19911015	<--	

GI



AB The title electrolytes are prepared by dissolving a solvent and an electrolyte salt in a trifunctional terminal acryloyl-modified alkylene oxide polymer containing a polymer chain described by the general formula I (R' = a low mol. weight alkyl group; R'' = H or Me; m, or n = 0 or an integer ≥ 1 ; and $m + n \geq 35$) and crosslinking it. The electrolytes are ion conductors and applications in cells, electrochromic displays, and sensors are indicated.

IT 115165-81-6P 118800-30-9P

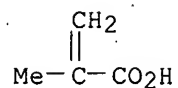
RL: PREP (Preparation)
 (preparation of, for electrolytes)

RN 115165-81-6 HCAPLUS

CN Oxirane, methyl-, polymer with oxirane, ether with 2-ethyl-2-(hydroxymethyl)-1,3-propanediol (3:1), 2-methyl-2-propenoate, block (9CI)
 (CA INDEX NAME)

CM 1

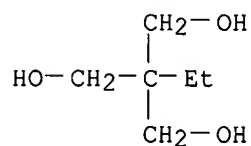
CRN 79-41-4
 CMF C4 H6 O2



CM 2

CRN 77-99-6

CMF C6 H14 O3



CM 3

CRN 106392-12-5

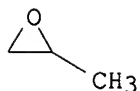
CMF (C3 H6 O . C2 H4 O)x

CCI PMS

CM 4

CRN 75-56-9

CMF C3 H6 O



CM 5

CRN 75-21-8

CMF C2 H4 O



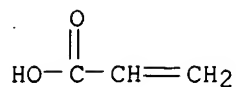
RN 118800-30-9 HCAPLUS

CN Oxirane, methyl-, polymer with oxirane, ether with 2-ethyl-2-(hydroxymethyl)-1,3-propanediol (3:1), 2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 79-10-7

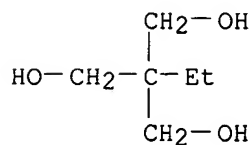
CMF C3 H4 O2



CM 2

CRN 77-99-6

CMF C6 H14 O3



CM 3

CRN 9003-11-6

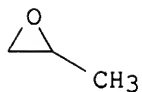
CMF (C3 H6 O . C2 H4 O)x

CCI PMS

CM 4

CRN 75-56-9

CMF C3 H6 O



CM 5

CRN 75-21-8

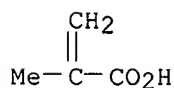
CMF C2 H4 O



L90 ANSWER 25 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN
 AN 1993:675100 HCAPLUS
 DN 119:275100
 TI Batteries with solid polymer electrolytes
 IN Kono, Michiyuki; Mori, Shigeo; Takeda, Kazunari; Izuti, Shyuiti
 PA Daiichi Kogyo Seiyaku Co., Ltd., Japan; Yuasa Corp.
 SO PCT Int. Appl., 29 pp.
 CODEN: PIXXD2
 DT Patent
 LA Japanese

FAN.CNT 1

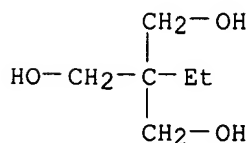
	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	WO 9314529	A1	19930722	WO 1993-JP64	19930120 <--
	W: CA, US				
	RW: AT, BE, CH, DE, DK, ES, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE				
	JP 05198303	A2	19930806	JP 1992-31451	19920121 <--
	EP 576686	A1	19940105	EP 1993-902505	19930120 <--
	EP 576686	B1	20011010		
	R: DE, FR, GB				
	JP 07006787	A2	19950110	JP 1993-26269	19930120 <--
	JP 3290229	B2	20020610		
	CA 2106205	C	19991214	CA 1993-2106205	19930120 <--
	US 5436090	A	19950725	US 1993-119214	19930921 <--
PRAI	JP 1992-31451	A	19920121	<--	
	WO 1993-JP64	W	19930120	<--	
AB	The batteries use electrolytes obtained by crosslinking a mixture containing a trifunctional group polymer, an electrolyte salt, and a solvent by energy beam irradiation and/or heating; where the polymer contains 3 functional polymer chains of (CH ₂ CH ₂ O) _m (CH ₂ CRHO) _n COCR ₁ :CH ₂ (R = C1-6 alkyl group, R ₁ = H or Me, m + n ≥ 35, and m or n may be 0), and the solvent is used at 220-950% the weight of the polymer. The batteries may use the electrolyte as separators and cathodes containing the electrolyte, or use anodes containing the electrolyte.				
IT	150604-34-5				
	RL: USES (Uses)				
	(crosslinked, electrolyte containing lithium salts and solvents and, for batteries)				
RN	150604-34-5 HCAPLUS				
CN	Oxirane, methyl-, polymer with oxirane, ether with 2-ethyl-2-(hydroxymethyl)-1,3-propanediol (3:1), tris(2-methyl-2-propenoate), block (9CI) (CA INDEX NAME)				
CM	1				
CRN	79-41-4				
CMF	C4 H6 O2				



CM 2

CRN 77-99-6

CMF C6 H14 O3

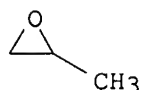


CM 3

CRN 106392-12-5
 CMF (C3 H6 O . C2 H4 O)x
 CCI PMS

CM 4

CRN 75-56-9
 CMF C3 H6 O



CM 5

CRN 75-21-8
 CMF C2 H4 O



L90 ANSWER 26 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN
 AN 1993:451269 HCAPLUS
 DN 119:51269
 TI Prevention of discoloration of unfixed dyes by combustion exhaust gases in
 dyeing or printing fabrics with reactive dyes
 IN Takekoshi, Shoji; Hashimoto, Akira; Tao, Kazuo
 PA Meisei Chemical Works, Ltd., Japan
 SO Jpn. Kokai Tokkyo Koho, 6 pp.
 CODEN: JKXXAF
 DT Patent
 LA Japanese
 FAN.CNT 1

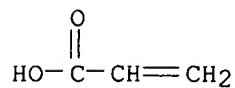
	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 04333676	A2	19921120	JP 1991-135446	19910510 <--
	JP 2549583	B2	19961030		
PRAI	JP 1991-135446		19910510 <--		

AB In the title process, cellulosic fabrics are dyed or printed with compns.
 containing CH₂:CRCO₂(CH₂CH₂O)_s(CH₂CHMeO)_pCOCR:CH₂ (R = Me, H; s = 5-20; p =
 0-10), CH₂:CRCO₂CH₂CH(OH)CH₂O(CH₂CH₂O)_s(CH₂CHMeO)_pCH₂CH(OH)CH₂CO₂CR:CH₂,
 MeCH₂C(CH₂OX)₃ [X = (CH₂CH₂O)_s(CH₂CHMeO)_pCOCR:CH₂], and/or YOCH₂C(CH₂OX)₃
 [Y = CH₂:CRCO(CH₂CH₂O)_s(CH₂CHMeO)_p]. A designed cotton broadcloth was
 dyed with a liquid containing polyoxyethylene dimethacrylate and Remazole
 Orange
 3R, dried, contacted with nitrogen oxide (g), and heat treated to give a
 colored fabric without discoloration.
 IT 117989-76-1
 RL: USES (Uses)
 (reactive dyeing solns. for cellulosic fabrics., for discoloration
 prevention)
 RN 117989-76-1 HCAPLUS
 CN Oxirane, methyl-, polymer with oxirane, ether with 2-ethyl-2-

(hydroxymethyl)-1,3-propanediol (3:1), tri-2-propenoate (9CI) (CA INDEX NAME)

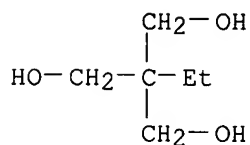
CM 1

CRN 79-10-7
CMF C3 H4 O2



CM 2

CRN 77-99-6
CMF C6 H14 O3

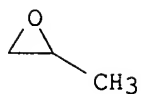


CM 3

CRN 9003-11-6
CMF (C3 H6 O . C2 H4 O) x
CCI PMS

CM 4

CRN 75-56-9
CMF C3 H6 O



CM 5

CRN 75-21-8
CMF C2 H4 O



L90 ANSWER 27 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN
AN 1993:410401 HCAPLUS

DN 119:10401
 TI Resist printing cellulosic fabrics with reactive dyes for sharp patterns
 IN Takekoshi, Shoji; Hashimoto, Akira; Tao, Kazuo
 PA Meisei Chemical Works, Ltd., Japan
 SO Jpn. Kokai Tokkyo Koho, 5 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 04343773	A2	19921130	JP 1991-141093	19910515 <--
	JP 2652475	B2	19970910		
PRAI	JP 1991-141093		19910515 <--		

AB In the title process, cellulosic fabrics are printed with compns. containing sulfurous acid salts, acidic sulfurous acid salts, and/or hydroxyalkanesulfonic acid salts as dye resist agents and subsequently printed with compns. containing reactive dyes containing vinyl sulfone groups, and

polyoxyalkylene (meth)acrylates with a specified structure as hollowing preventive agents. A cotton broadcloth was printed with a composition containing

Cibacron Red B and 3.0% Na2SO3, subsequently printed with a composition containing

Sumifix Brilliant Blue R and 2.0% polyoxyethylene diacrylate, and heat treated 8 min at 100° to give a resist-printed fabric with a sharp pattern.

IT 117989-76-1

RL: USES (Uses)

(resist printing compns. containing, for cotton fabrics, for sharp patterns)

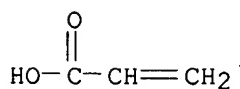
RN 117989-76-1 HCAPLUS

CN Oxirane, methyl-, polymer with oxirane, ether with 2-ethyl-2-(hydroxymethyl)-1,3-propanediol (3:1), tri-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 79-10-7

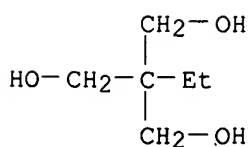
CMF C3 H4 O2



CM 2

CRN 77-99-6

CMF C6 H14 O3



CM 3

CRN 9003-11-6

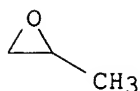
CMF (C3 H6 O . C2 H4 O)x

CCI PMS

CM 4

CRN 75-56-9

CMF C3 H6 O



CM 5

CRN 75-21-8

CMF C2 H4 O



L90 ANSWER 28 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN
 AN 1979:7044 HCAPLUS
 DN 90:7044
 TI Stable suspensions of inorganic filler in organic polyhydroxyl compounds
 IN Von Bonin, Wulf
 PA Bayer A.-G., Fed. Rep. Ger.
 SO Ger. Offen., 44 pp.
 CODEN: GWXXBX
 DT Patent
 LA German
 FAN.CNT 2

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	DE 2714291	A1	19781005	DE 1977-2714291	19770331 <--
	US 4207227	A	19800610	US 1977-856075	19771130 <--
	SE 7713638	A	19780604	SE 1977-13638	19771201 <--
	FR 2372851	A1	19780630	FR 1977-36404	19771202 <--
	GB 1583457	A	19810128	GB 1977-50304	19771202 <--
	JP 53071189	A2	19780624	JP 1977-144639	19771203 <--
	ES 464700	A1	19781101	ES 1977-464700	19771205 <--
PRAI	DE 1976-2654746	A	19761203	<--	
	DE 1977-2714291	A	19770331	<--	

AB The title compns., useful in polyurethane prepns., contain 0.5-80% inorg. filler and 99.5-20% (cyclo)aliphatic polyol grafted with 0.01-35% unsatd. carboxylic acid and 0-25% comonomer (polyol CO2H content 0.005-15%). Thus, stirring polyethylene-polypropylene glycol trimethylolpropane ether (3:1) (I) (mol. weight 4800, primary OH content <3%) 200, styrene 10, acrylic acid 20, and tert-Bu peroxyoctanoate 0.5 part 4 h at 90° gave a clear, viscous graft polymer (II) [67184-04-7]. A suspension of 80 parts

CaCO₃ (average particle size 3 μ) in 400 parts I and 52 parts II showed 0.5% settling in 15 days at 21°, compared with 65% in the absence of II.

IT 67183-99-7 67184-01-4

RL: USES (Uses)

(graft, dispersing agents, for suspensions of inorg. fillers in polyols)

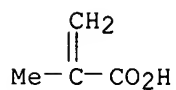
RN 67183-99-7 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, polymer with methyloxirane polymer with oxirane ether with 2-ethyl-2-(hydroxymethyl)-1,3-propanediol (3:1) and 2-propenoic acid (9CI) (CA INDEX NAME)

CM 1

CRN 79-41-4

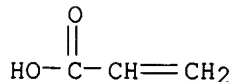
CMF C4 H6 O2



CM 2

CRN 79-10-7

CMF C3 H4 O2



CM 3

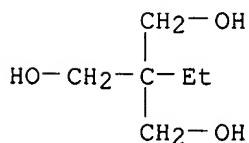
CRN 52624-57-4

CMF C6 H14 O3 . 3 (C3 H6 O . C2 H4 O)x

CM 4

CRN 77-99-6

CMF C6 H14 O3



CM 5

CRN 9003-11-6

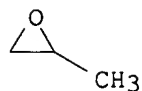
CMF (C3 H6 O . C2 H4 O)x

CCI PMS

CM 6

CRN 75-56-9

CMF C3 H6 O



CM 7

CRN 75-21-8

CMF C2 H4 O



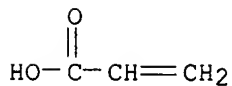
RN 67184-01-4 HCAPLUS

CN 2-Propenoic acid, polymer with methyloxirane polymer with oxirane ether
with 2-ethyl-2-(hydroxymethyl)-1,3-propanediol (3:1) (9CI) (CA INDEX
NAME)

CM 1

CRN 79-10-7

CMF C3 H4 O2



CM 2

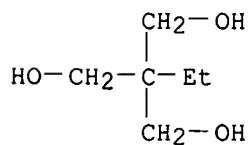
CRN 52624-57-4

CMF C6 H14 O3 . 3 (C3 H6 O . C2 H4 O) x

CM 3

CRN 77-99-6

CMF C6 H14 O3

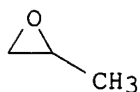


CM 4

CRN 9003-11-6
 CMF (C3 H6 O . C2 H4 O)x
 CCI PMS

CM 5

CRN 75-56-9
 CMF C3 H6 O



CM 6

CRN 75-21-8
 CMF C2 H4 O



L90 ANSWER 29 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN
 AN 1978:511127 HCAPLUS
 DN 89:111127
 TI Stable suspensions of inorganic fillers in organic polyhydroxyl compounds
 IN Von Bonin, Wulf
 PA Bayer A.-G., Fed. Rep. Ger.
 SO Ger. Offen., 32 pp.
 CODEN: GWXXBX

DT Patent
 LA German

FAN.CNT 2

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	DE 2654746	A1	19780608	DE 1976-2654746	19761203 <--
	US 4207227	A	19800610	US 1977-856075	19771130 <--
	SE 7713638	A	19780604	SE 1977-13638	19771201 <--
	BE 861425	A1	19780602	BE 1977-183104	19771202 <--
	FR 2372851	A1	19780630	FR 1977-36404	19771202 <--
	GB 1583457	A	19810128	GB 1977-50304	19771202 <--
	JP 53071189	A2	19780624	JP 1977-144639	19771203 <--
	ES 464700	A1	19781101	ES 1977-464700	19771205 <--
PRAI	DE 1976-2654746	A	19761203	<--	
	DE 1977-2714291	A	19770331	<--	

AB Polyols grafted with (meth)acrylic acid and, in some cases, other vinyl monomers were used to stabilize suspensions of inorg. fillers in polyols. These suspensions were useful for the manufacture of polyurethanes. Thus, a polyol (I) (mol. weight 4800) prepared from (HOCH2)3CEt, ethylene oxide, and propylene oxide was grafted (200 parts) with 10 parts styrene and 20 parts acrylic acid, and 52 parts graft copolymer was mixed with 400 parts I and 80 parts CaCO3 filler to prepared a stable suspension.

IT 67183-99-7 67184-01-4
 RL: USES (Uses)

(graft, for stabilization of polyol-filler suspensions for polyurethane manufacture)

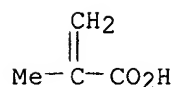
RN 67183-99-7 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, polymer with methyloxirane polymer with oxirane ether with 2-ethyl-2-(hydroxymethyl)-1,3-propanediol (3:1) and 2-propenoic acid (9CI) (CA INDEX NAME)

CM 1

CRN 79-41-4

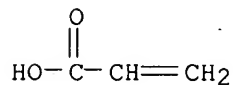
CMF C4 H6 O2



CM 2

CRN 79-10-7

CMF C3 H4 O2



CM 3

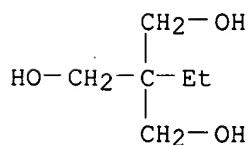
CRN 52624-57-4

CMF C6 H14 O3 . 3 (C3 H6 O . C2 H4 O)x

CM 4

CRN 77-99-6

CMF C6 H14 O3



CM 5

CRN 9003-11-6

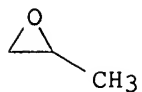
CMF (C3 H6 O . C2 H4 O)x

CCI PMS

CM 6

CRN 75-56-9

CMF C3 H6 O



CM 7

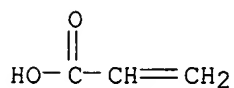
CRN 75-21-8
CMF C2 H4 O



RN 67184-01-4 HCAPLUS
CN 2-Propenoic acid, polymer with methyloxirane polymer with oxirane ether
with 2-ethyl-2-(hydroxymethyl)-1,3-propanediol (3:1) (9CI) (CA INDEX
NAME)

CM 1

CRN 7,9-10-7
CMF C3 H4 O2

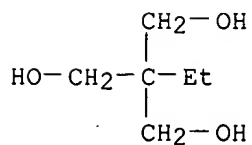


CM 2

CRN 52624-57-4
CMF C6 H14 O3 . 3 (C3 H6 O . C2 H4 O)x

CM 3

CRN 77-99-6
CMF C6 H14 O3



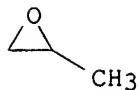
CM 4

CRN 9003-11-6
CMF (C3 H6 O . C2 H4 O)x
CCI PMS

CM 5

CRN 75-56-9

CMF C3 H6 O



CM 6

CRN 75-21-8

CMF C2 H4 O



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(FILE 'HOME' ENTERED AT 06:38:22 ON 16 NOV 2006)
SET COST OFF

FILE 'HCAPLUS' ENTERED AT 06:38:40 ON 16 NOV 2006

L1 7 S US20050215752/PN OR (US2004-517042# OR WO2003-EP5953 OR DE200
SEL RN

FILE 'REGISTRY' ENTERED AT 06:40:04 ON 16 NOV 2006

L2 75 S E1-E75
L3 1 S L2 AND C6H14O3/MF
L4 17006 S 77-99-6/CRN
L5 1559 S L4 AND (79-10-7 OR 79-41-4)/CRN
L6 215 S L5 AND C2H4O
L7 104 S L6 AND C3H6O
L8 98 S L7 AND 75-21-8/CRN
L9 0 S L7 AND 25322-68-3/CRN
L10 97 S L8 AND 75-56-9/CRN
L11 2 S L8 AND (31714-45-1 OR 25322-69-4)/CRN
L12 98 S L10,L11
L13 6 S L7 NOT L12
L14 39 S L12 NOT C6/ES
L15 36 S L14 NOT 56-81-5/CRN
L16 34 S L15 NOT OC4-C6/ES
SEL RN 4 5 8 9 14 17 18 25 27 29-31 33
L17 13 S E76-E88
L18 21 S L16 NOT L17
L19 16 S L2 AND L4
L20 6 S L19 NOT L18
SAV L18 TRUONG517/A
L21 STR
L22 50 S L21
L23 35943 S L21 FUL
L24 STR
L25 50 S L24 SAM SUB=L23

L26 15579 S L24 FUL SUB=L23
 L27 499 S L26 AND (75-21-8 OR 25322-68-3)/CRN
 L28 2681 S L26 AND C2H4O
 L29 2681 S L27,L28
 L30 266 S L29 AND (75-56-9 OR 31714-45-1 OR 25322-69-4)/CRN
 L31 431 S L29 AND C3H6O
 L32 431 S L30,L31
 L33 154 S L32 NOT (C6 OR OC4-C6)/ES
 L34 117 S L33 NOT L12
 L35 111 S L34 NOT OC4/ES
 L36 39 S L35 AND (N OR S OR SI OR P)/ELS
 L37 72 S L35 NOT L36
 L38 70 S L37 NOT 56-81-5/CRN
 L39 65 S L38 NOT C4H4O4
 L40 34 S L39 NOT (UNSPECIFIED OR C5-C6-C6-C6/ES)
 L41 6 S L40 AND NR>=3
 L42 28 S L40 NOT L41
 SEL RN 2 4-9 11 16 18 19 21 23-28
 L43 10 S L42 NOT E89-E106
 L44 STR L24
 L45 50 S L44 SAM SUB=L26
 L46 STR L44
 L47 50 S L46 CSS SAM SUB=L26
 L48 SCR 1992 OR 2021 OR 2016 OR 2026 OR 1852 OR 1855 OR 1867
 L49 50 S L46 NOT L48 CSS SAM SUB=L26
 L50 1830 S L46 NOT L48 CSS FUL SUB=L26
 L51 1762 S L50 NOT (C6-C6 OR C5-C6 OR OC4-C6)/ES
 L52 524 S L51 AND L29 NOT L32
 L53 336 S L52 NOT UNSPECIFIED
 L54 0 S L53 AND (C2H4O AND C3H6O)
 L55 STR L46
 L56 21 S L55 CSS SAM SUB=L50
 L57 427 S L55 CSS FUL SUB=L50
 L58 135 S L57 AND (C2H4O OR C3H6O)
 L59 24 S L58 AND NR>=2
 L60 3 S L59 AND C15H24O6 NOT UNSPECIFIED
 SEL RN 1
 L61 1 S E107
 L62 111 S L58 NOT L59
 L63 57 S L62 NOT UNSPECIFIED
 SEL RN 5 15 19 30 32 34 48
 L64 7 S E108-E114
 L65 37 S L18,L43,L61,L64
 L66 47 S L2 AND PMS/CI
 L67 37 S L66 NOT L65
 L68 29 S L67 NOT 56-81-5/CRN
 SEL RN 2 8
 L69 2 S E115-E116
 L70 39 S L65,L69
 L71 28 S L2 NOT L66,L70
 SAV L70 TRUONG517A/A

FILE 'HCAPLUS' ENTERED AT 07:51:53 ON 16 NOV 2006

L72 41 S L70
 L73 5 S L72 AND (POPP ? OR DANIEL ? OR SCHRODER ? OR JAWOREK ? OR FUN
 L74 8 S L72 AND BASF?/PA,CS
 L75 8 S L73,L74
 L76 3 S L72 NOT P/DT
 L77 30 S L72 NOT L75,L76
 L78 26 S L77 AND (PD<=20030606 OR PRD<=20030606 OR AD<=20030606)

L79 26 S L77 AND (PD<=20020611 OR PRD<=20020611 OR AD<=20020611)
L80 29 S L76,L78,L79
L81 4 S L77 NOT L80
SEL RN L75

FILE 'REGISTRY' ENTERED AT 07:55:49 ON 16 NOV 2006

L82 90 S E117-E206
L83 28 S L82 NOT L2
L84 8 S L83 AND L4
L85 5 S L84 NOT C6/ES
L86 3 S L85 NOT (117801-97-5 OR 117801-93-1)

FILE 'HCAPLUS' ENTERED AT 07:58:08 ON 16 NOV 2006

L87 2 S L86
L88 37 S L87,L75,L80
L89 8 S L88 AND L75
L90 29 S L88 NOT L89
L91 8 S L89 AND (PD<=20020611 OR PRD<=20020611 OR AD<=20020611)

FILE 'REGISTRY' ENTERED AT 07:59:10 ON 16 NOV 2006

FILE 'HCAPLUS' ENTERED AT 07:59:48 ON 16 NOV 2006

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